

Focusing neutron optics with elastically bent perfect crystals

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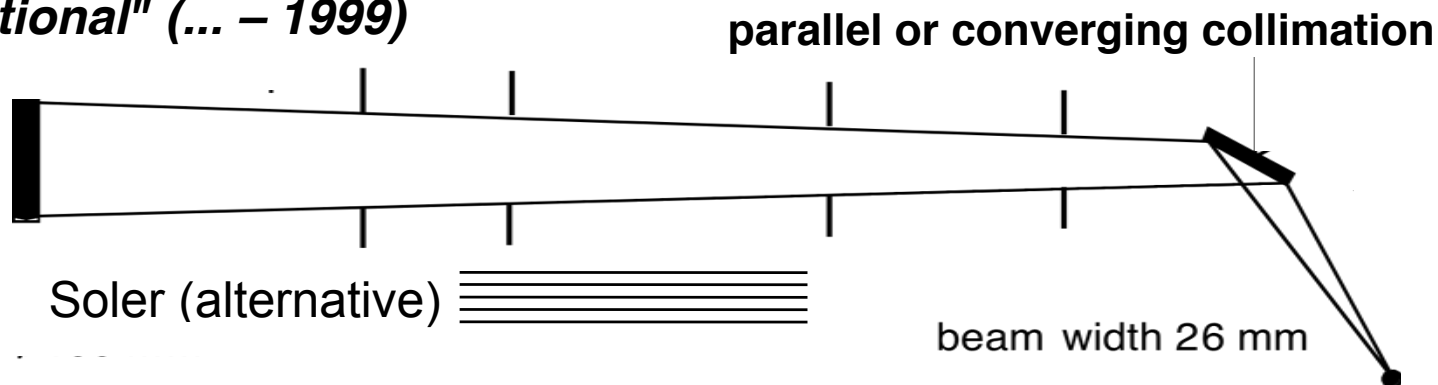
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Layout of the talk

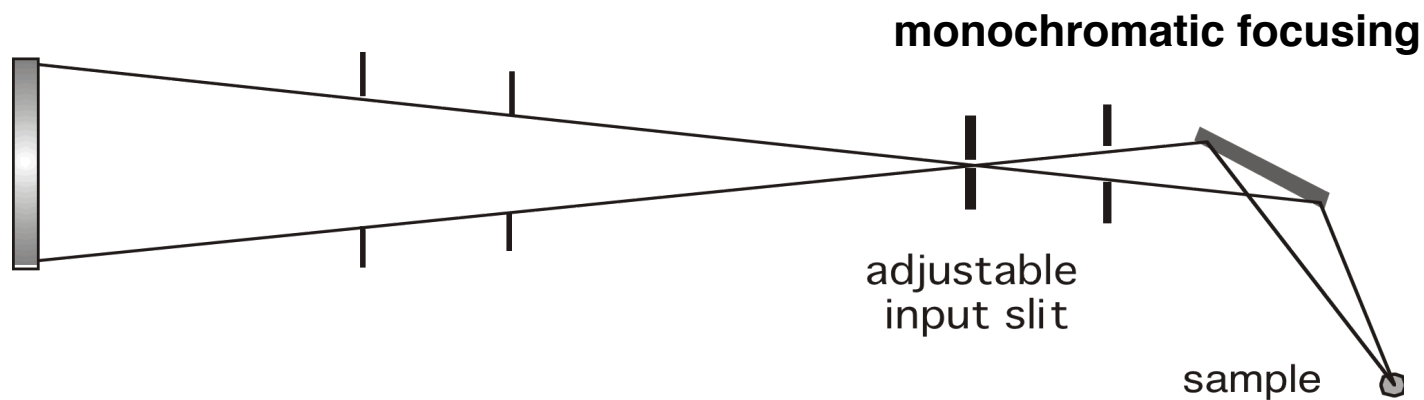
- 1. Optics**
- 2. Technology**
- 3. Applications**
 - 1. General TAS**
 - 2. Fine focusing reciprocal space**
 - 3. Fine focusing real space**
- 4. Conclusions**

TAS layout

"traditional" (... - 1999)



"modern" (2000 - ...)



intensity gain $\approx 30x$

sample size $> 1 \text{ cm}^3 \rightarrow 100 \text{ mm}^3$

Mosaic crystal

assembly of (slightly) misaligned blocks

Zachariasen's equations:

$$\frac{\partial I_0}{\partial s_0} = -\sigma(\varepsilon)(I_0 - I_G)$$

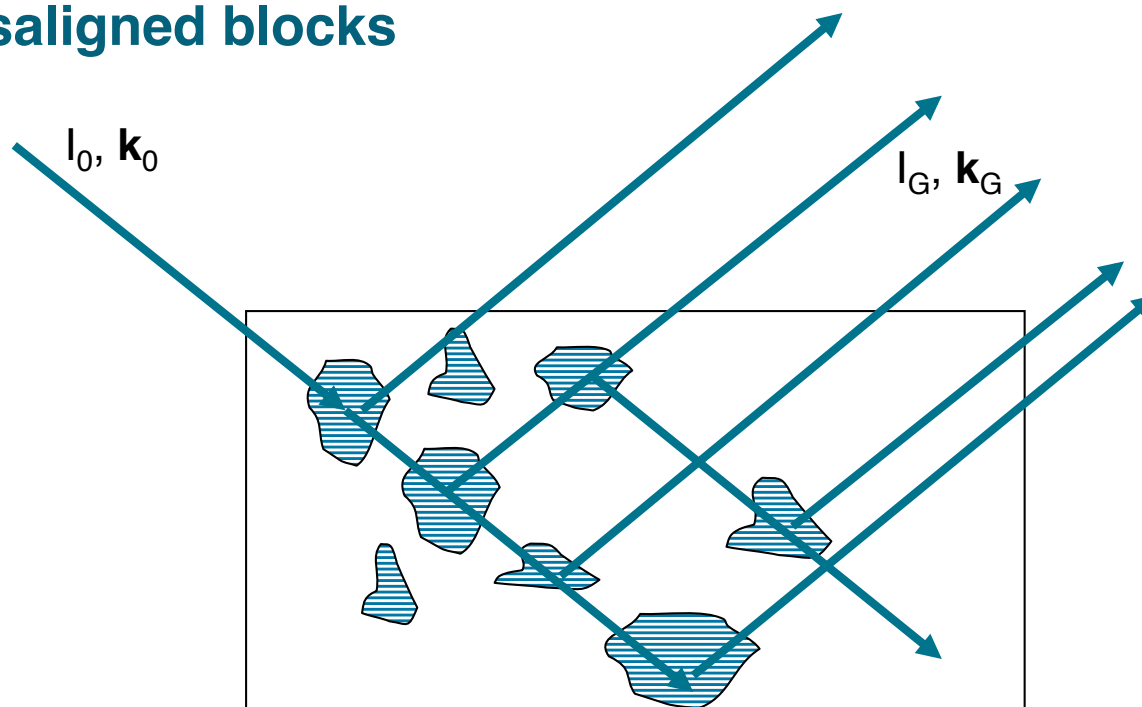
$$\frac{\partial I_G}{\partial s_G} = -\sigma(\varepsilon)(I_G - I_0)$$

$$\sigma(\varepsilon) = Q_{kin} w(\varepsilon) = \frac{F_G^2 \lambda^3}{v_0^2 \sin 2\theta} \frac{\exp\left[-(\varepsilon/\eta)^2\right]}{\eta\sqrt{\pi}}$$

kinematic reflectivity

mosaic distribution (Gaussian)

angular deviation



$$\varepsilon = \Theta - \Theta_0$$

Mosaic crystal reflectivity

Solutions to Zachariasen's eqs:

Bragg case:

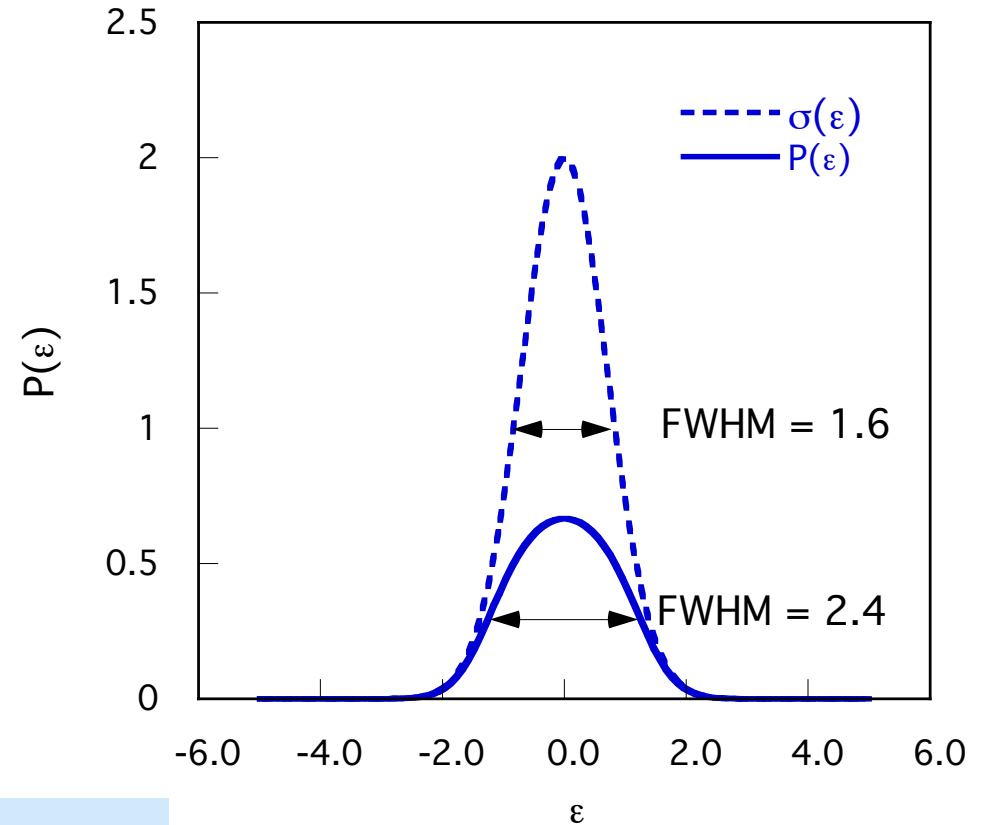
$$P(\varepsilon) = \frac{\sigma(\varepsilon)}{\mu + \sigma(\varepsilon) + u(\varepsilon) \coth ut}$$

$$P(\varepsilon) = \frac{\sigma(\varepsilon)}{\sigma(\varepsilon) + 1}, \quad \mu = 0$$

$$u = \sqrt{\mu(\mu + 2\sigma)}$$

Laue case:

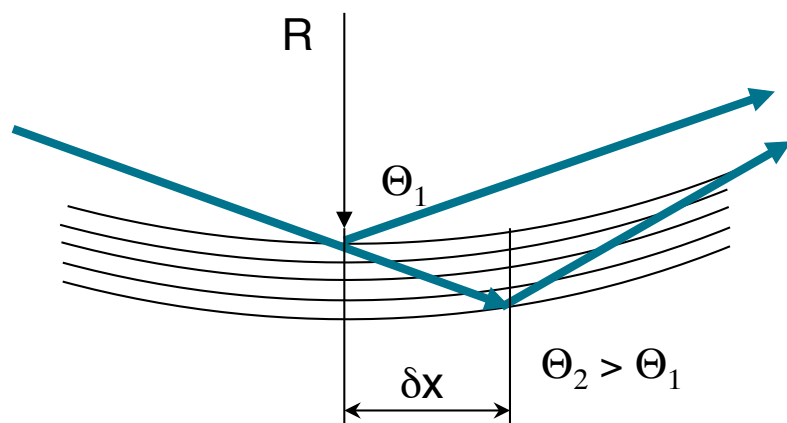
$$P(\varepsilon) = \exp[-(\mu + \sigma(\varepsilon))t] \sinh[\sigma(\varepsilon)t]$$



$$\sigma(\varepsilon) = Q_{kin} w(\varepsilon) = \frac{F_g^2 \lambda^3}{v_0^2 \sin 2\theta} \frac{\exp[-(\varepsilon/\eta)^2]}{\eta \sqrt{\pi}}$$

Gradient crystals

Simple bending

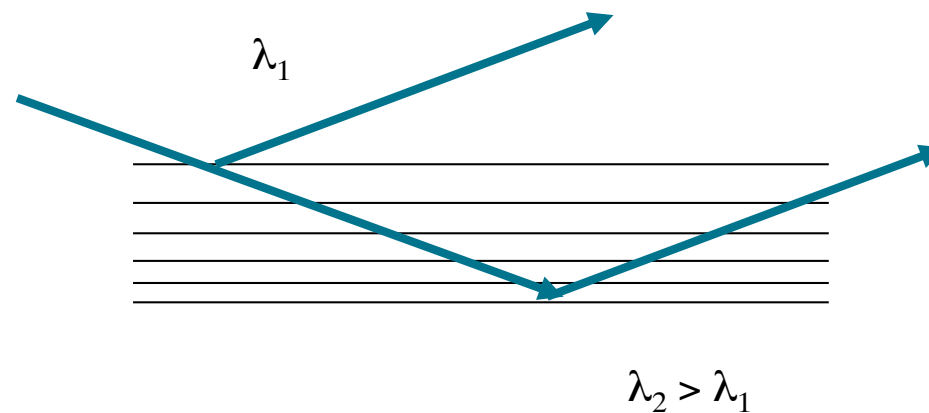


apparent mosaic width:

$$\delta\Theta = \frac{\delta x}{R}$$

wavelength band:

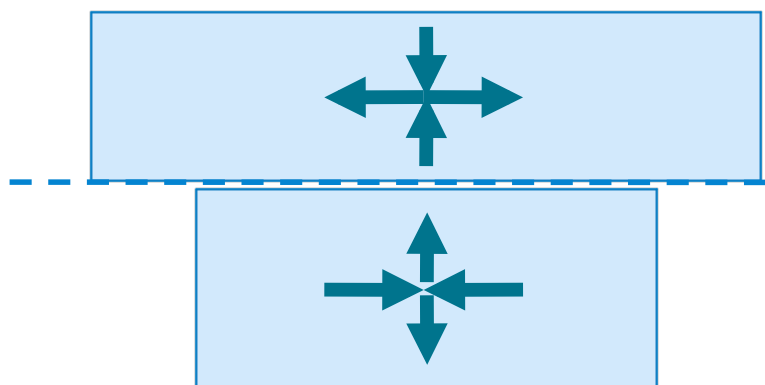
$$\Delta\lambda = 2\Delta d_{hkl} \sin\Theta$$



Simple d_{hkl} gradient)

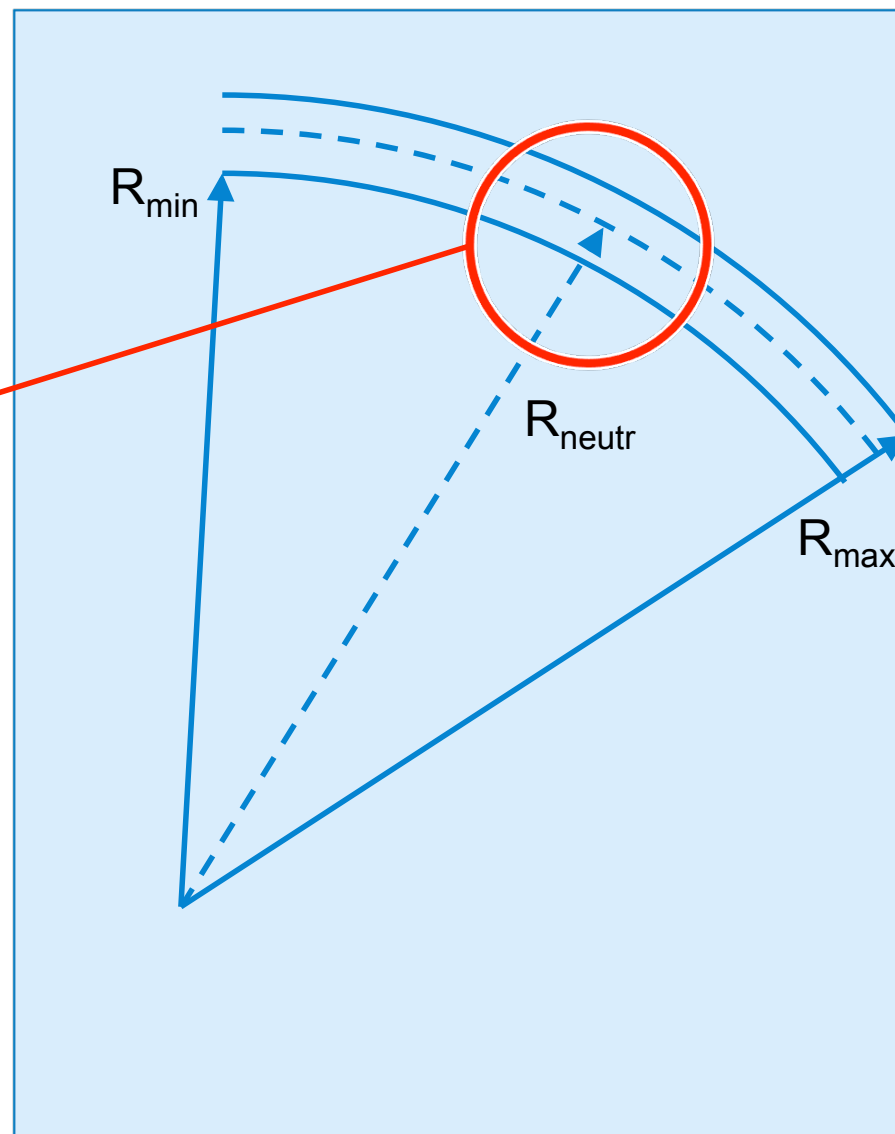
Gradient crystals

Elastically bent crystal

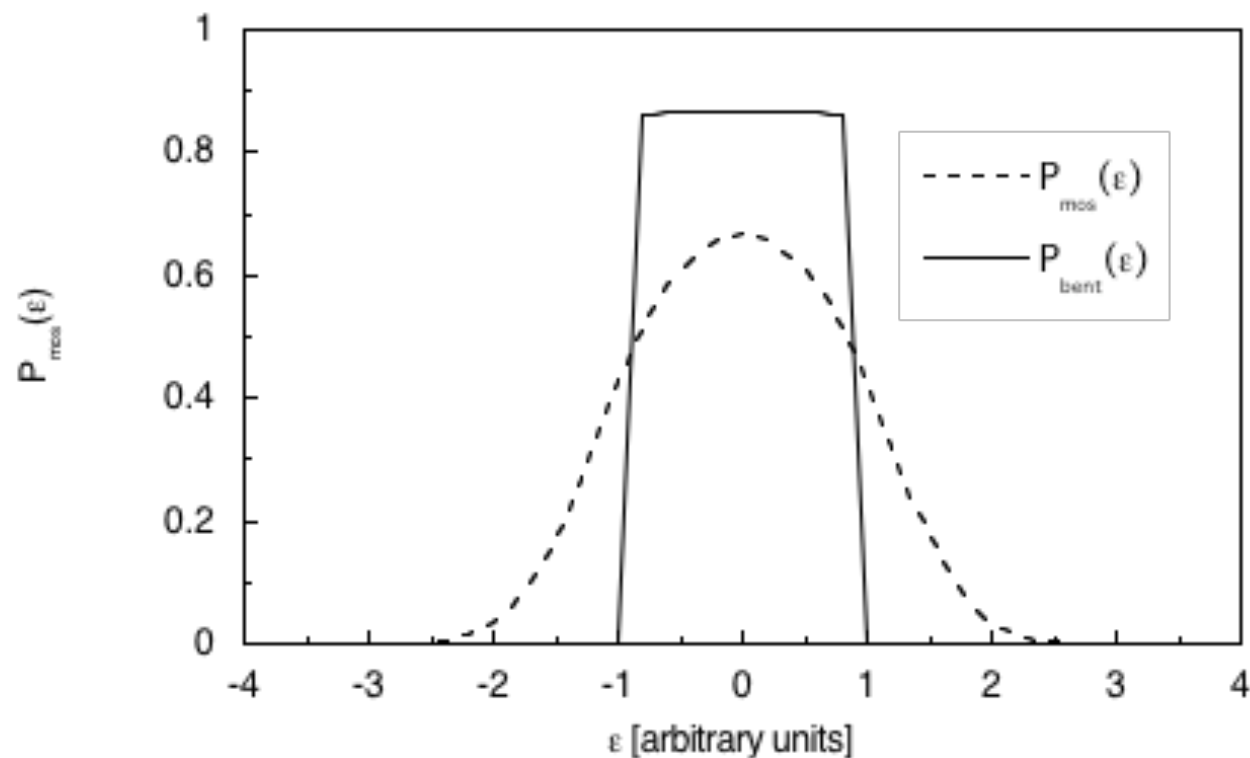


Effective bending radius variation
due to strain/stress equilibrium

analytically solvable
(cf. eg. Landau & Lifshitz)



Reflection profile



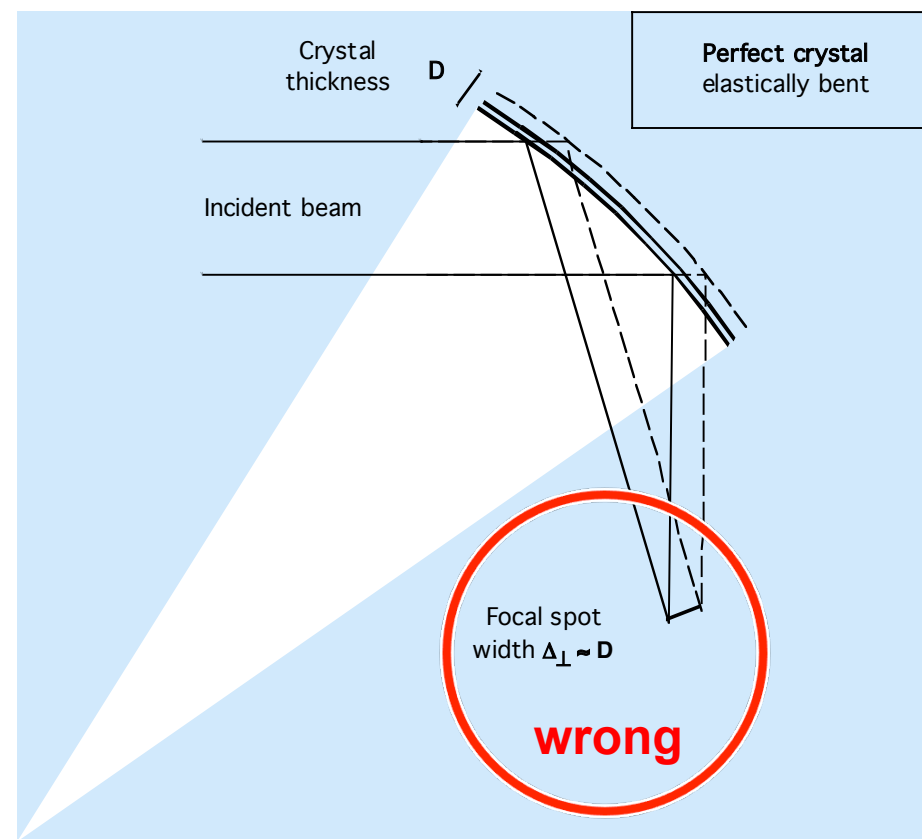
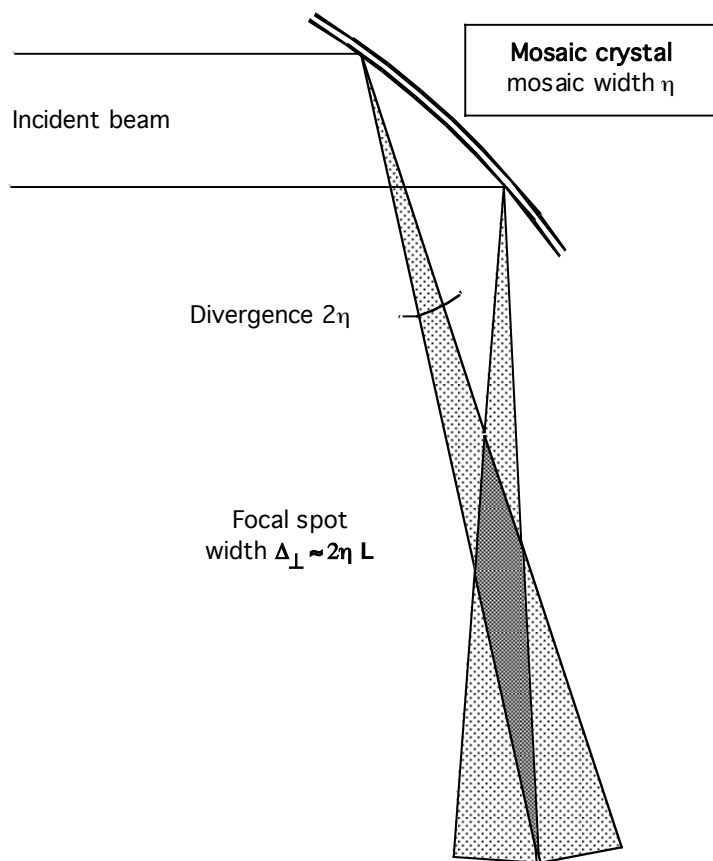
Integrated reflectivity

$$\rho(\Theta) = \frac{\Delta x}{R} \left[1 - \exp\left(\frac{Q_{kin} R}{\cos \Theta}\right) \right]$$

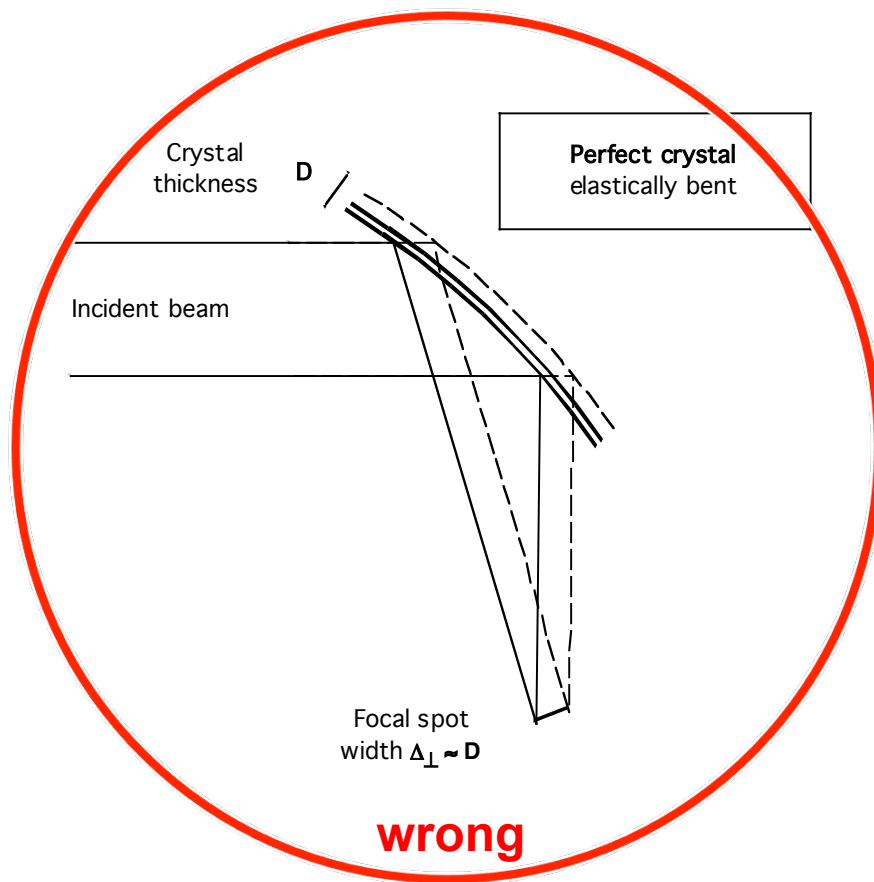
- almost rectangular rocking curve with minimum tails
- smaller crystal thickness required to achieve given reflectivity

Focusing properties

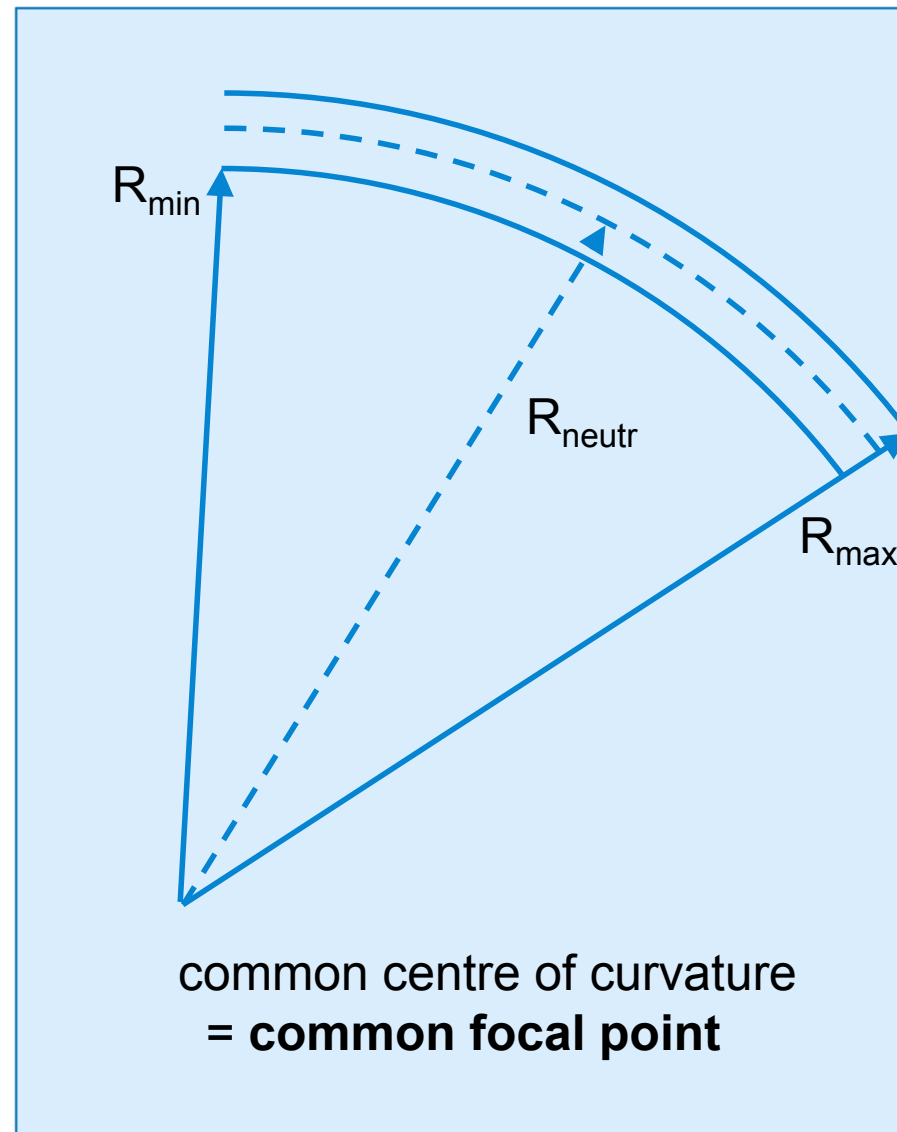
real space



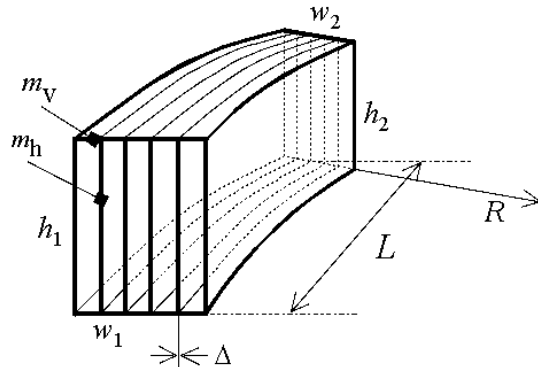
Gradient crystals



Kulda & Saroun, Nucl. Inst. Meth. A379 (1996) 155

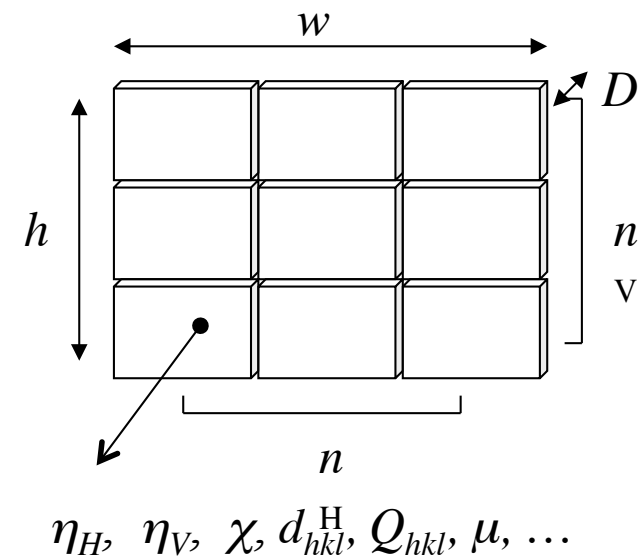
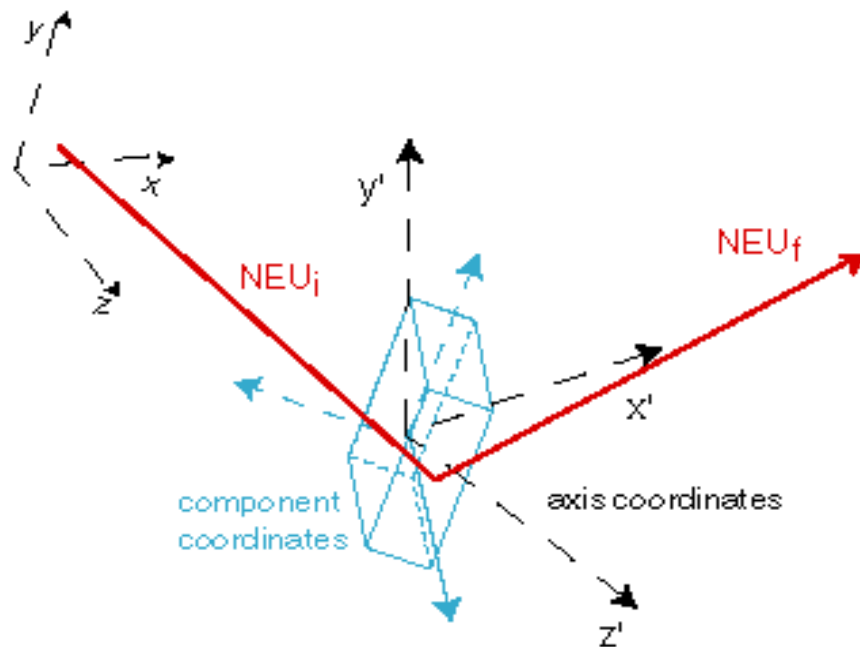


RESTRAX



- neutron ray-tracing or multi-Gaussian convolution
- diffraction/reflection optics of neutron instruments
- realistic crystal description (mosaic, elastically bent)
- highly optimized F77/F95 code

<http://omega.ujf.cas.cz/restrax>



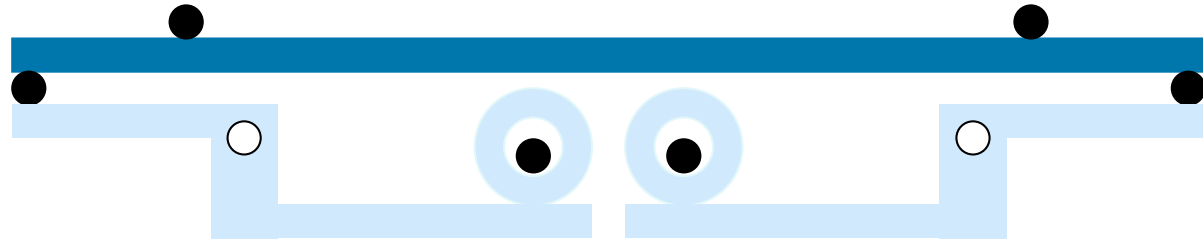
Layout of the talk

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2. Technology
3. Applications
 1. General TAS
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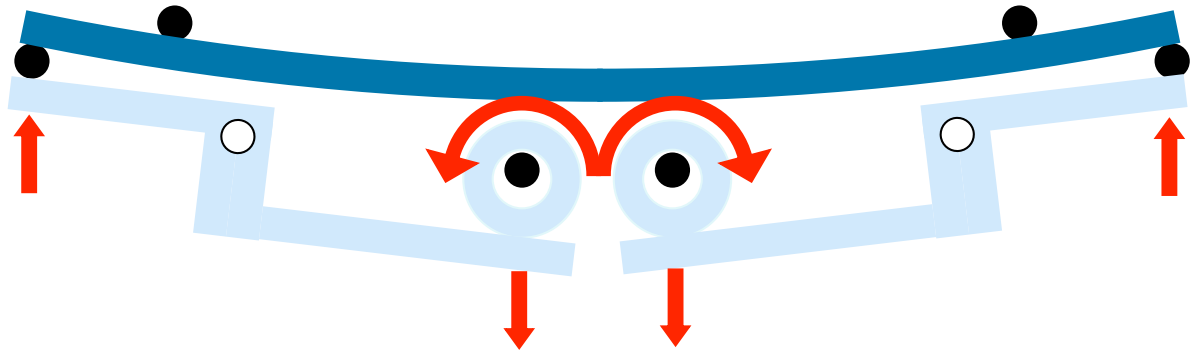
Si bender - function scheme

- **horizontal focusing:** four-point bending device

$R_h = \text{inf.}$



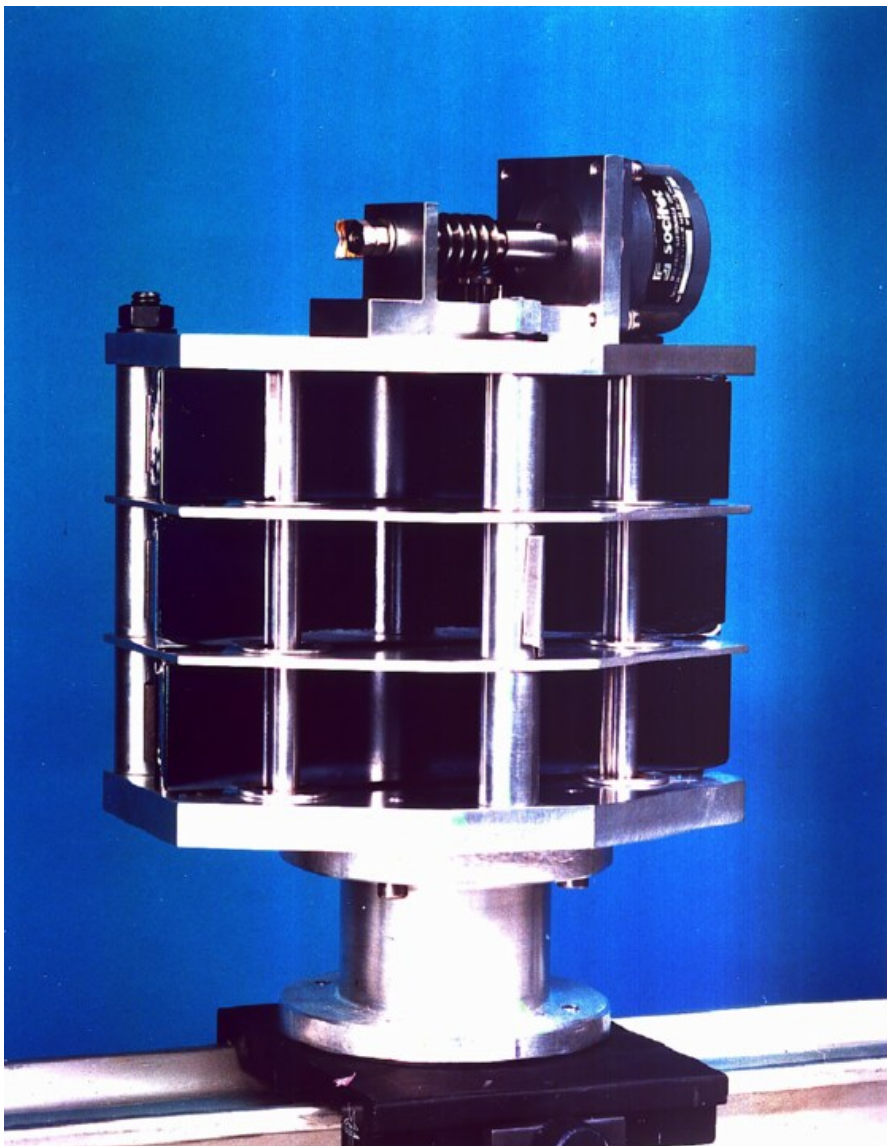
$R_h = 1 - 20 \text{ m}$



- **vertical focusing:** inclining segments & bell-shaped cams

$R_v = 0.2 \text{ m} - \text{inf.}$

Si bender - 1st generation



1st generation:

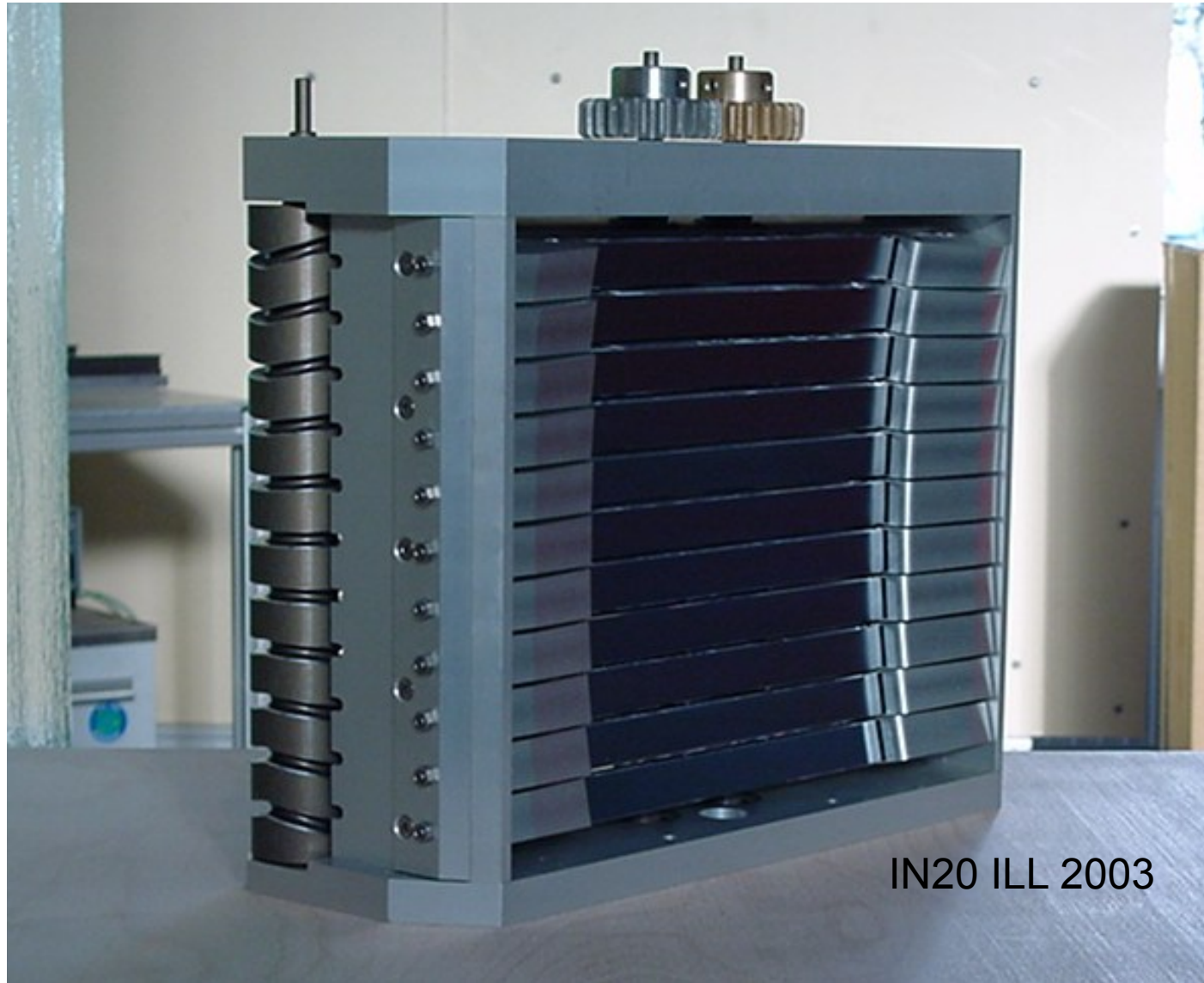
- variable horizontal curvature
- fixed vertical curvature
- 3 vertical segments (40 mm)
- blade thickness 3-5 mm
- active length 120 mm



2nd generation:

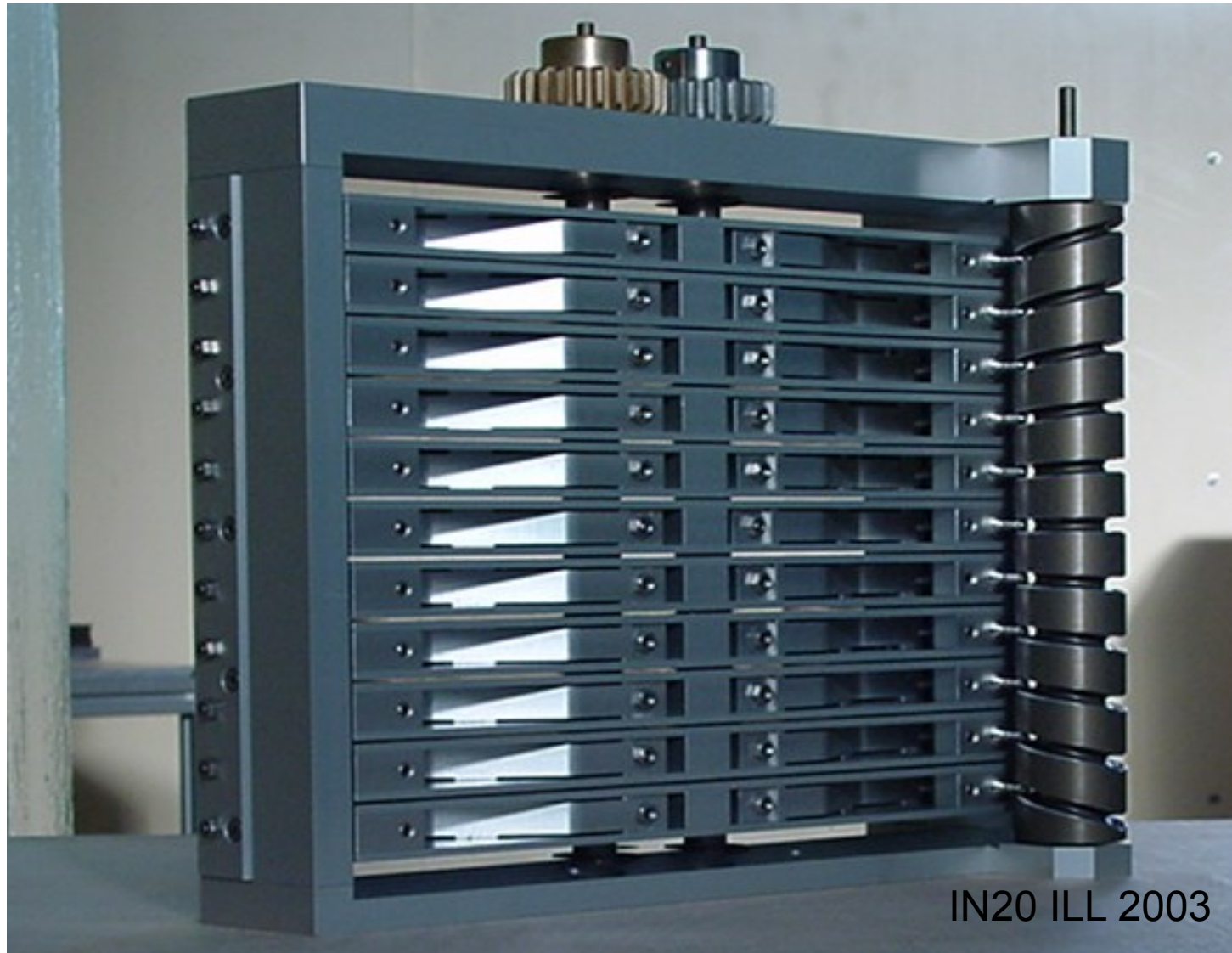
- *variable horizontal AND vertical curvature*
- *segment height < 20 mm*
- *blade thickness < 1 mm*
(> 10 per pack)

Si bender - front



IN20 ILL 2003

Si bender - back



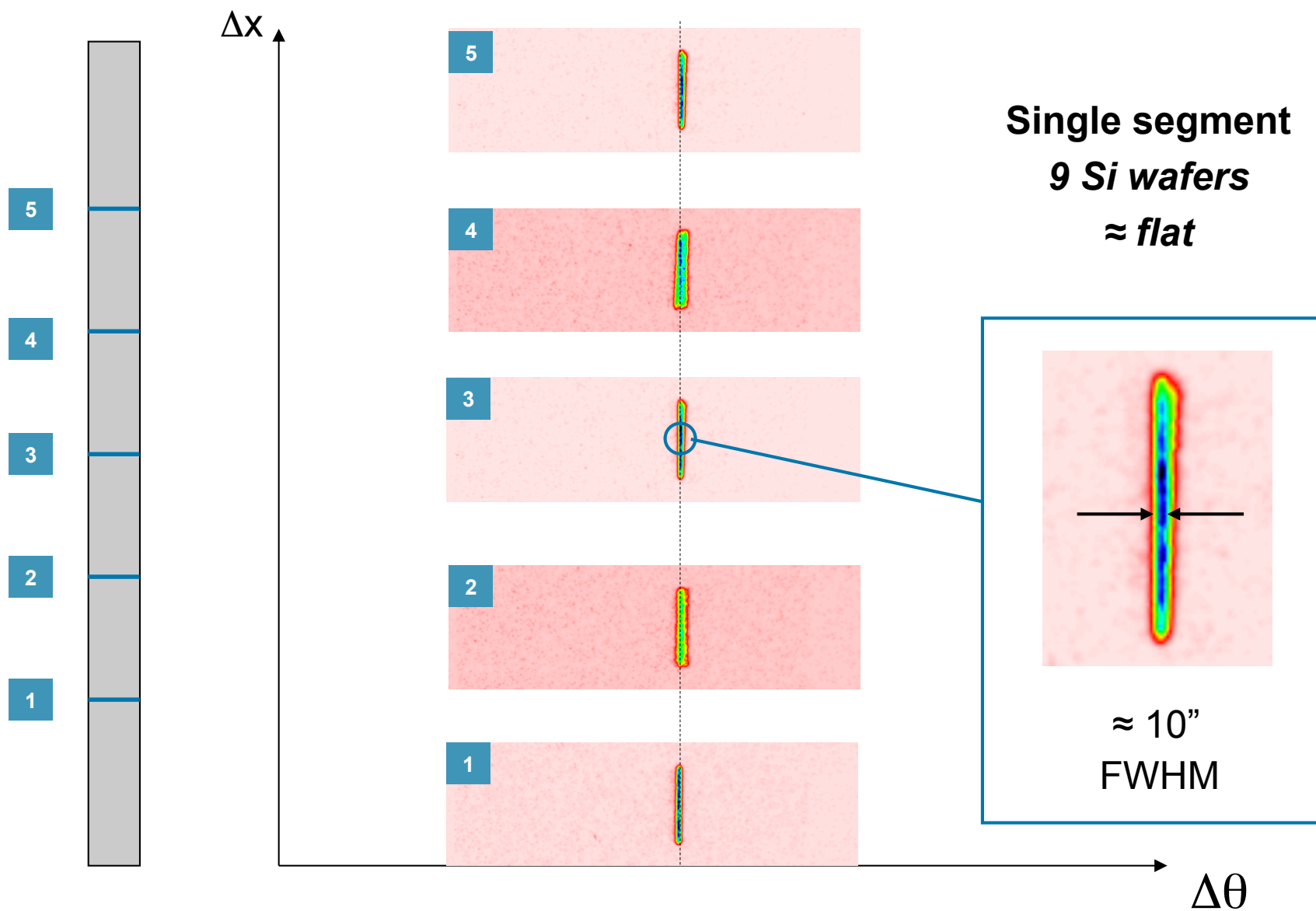
IN20 ILL 2003

Si wafers

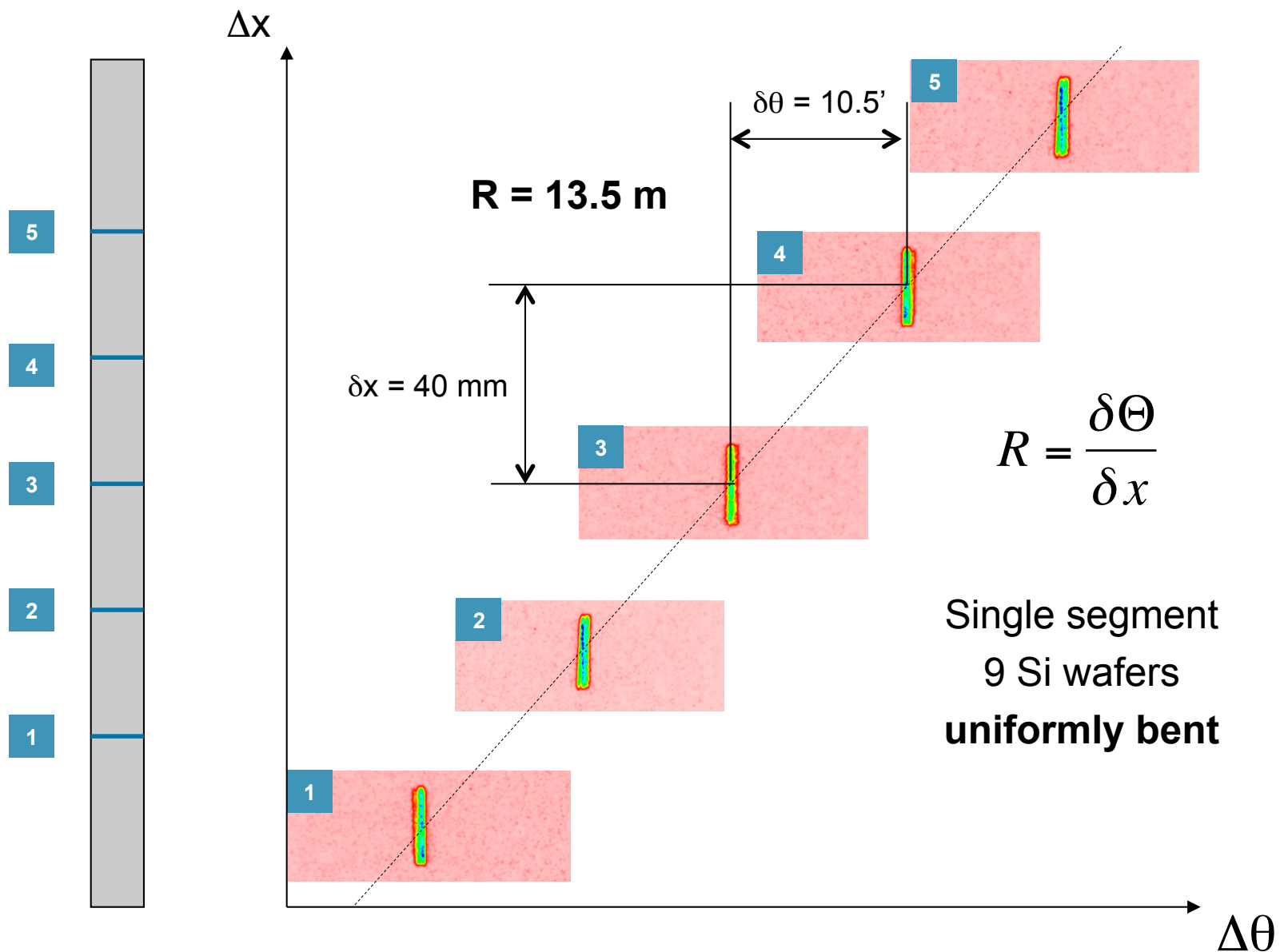
- 99 wafers (11 segments, 9 wafers each)
- size 265 x 17 x 1 mm³
- largest face (111)
- surface as-cut (mutiwire saw!) & etched



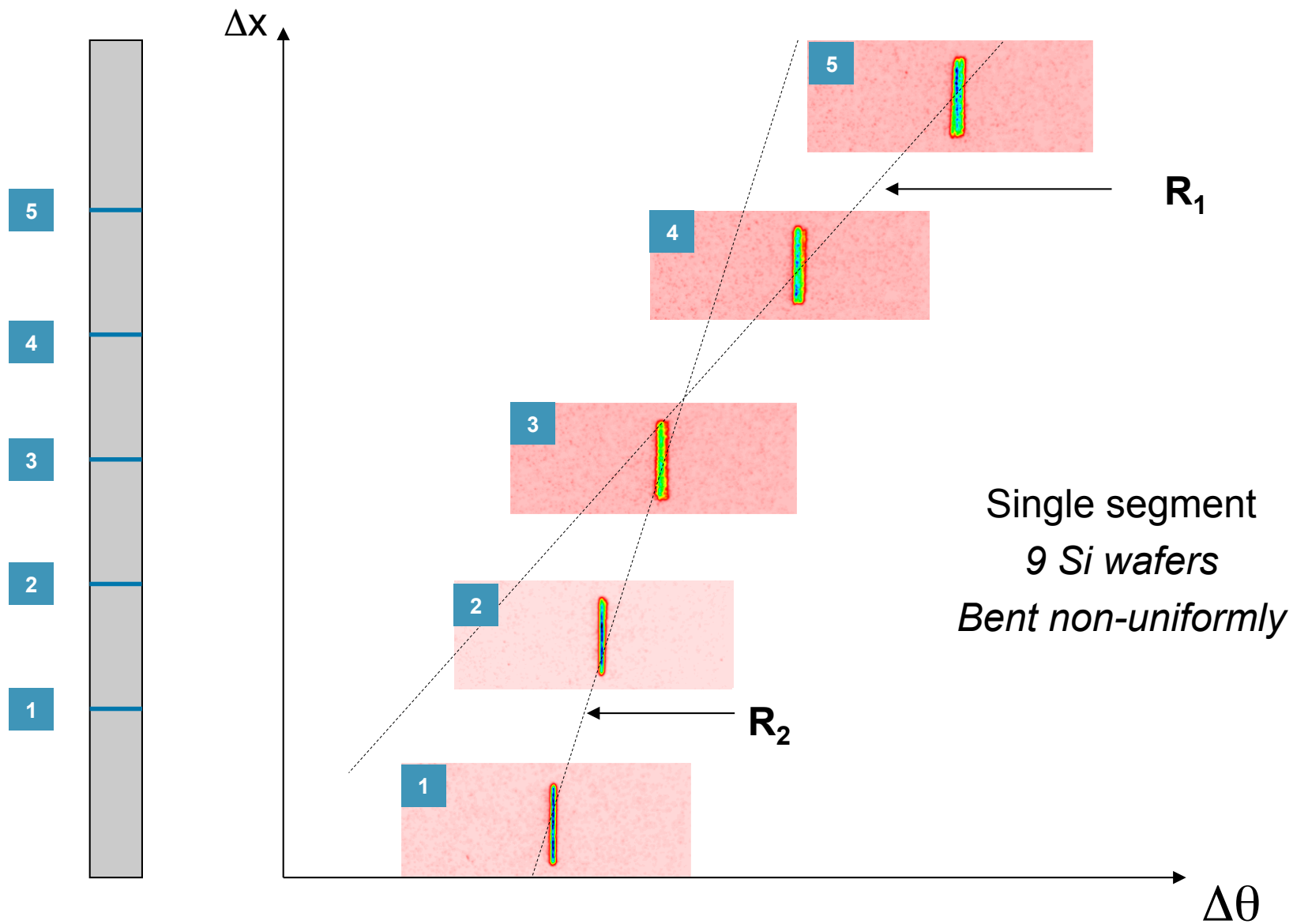
X-ray tests (I)



X-ray tests (II)



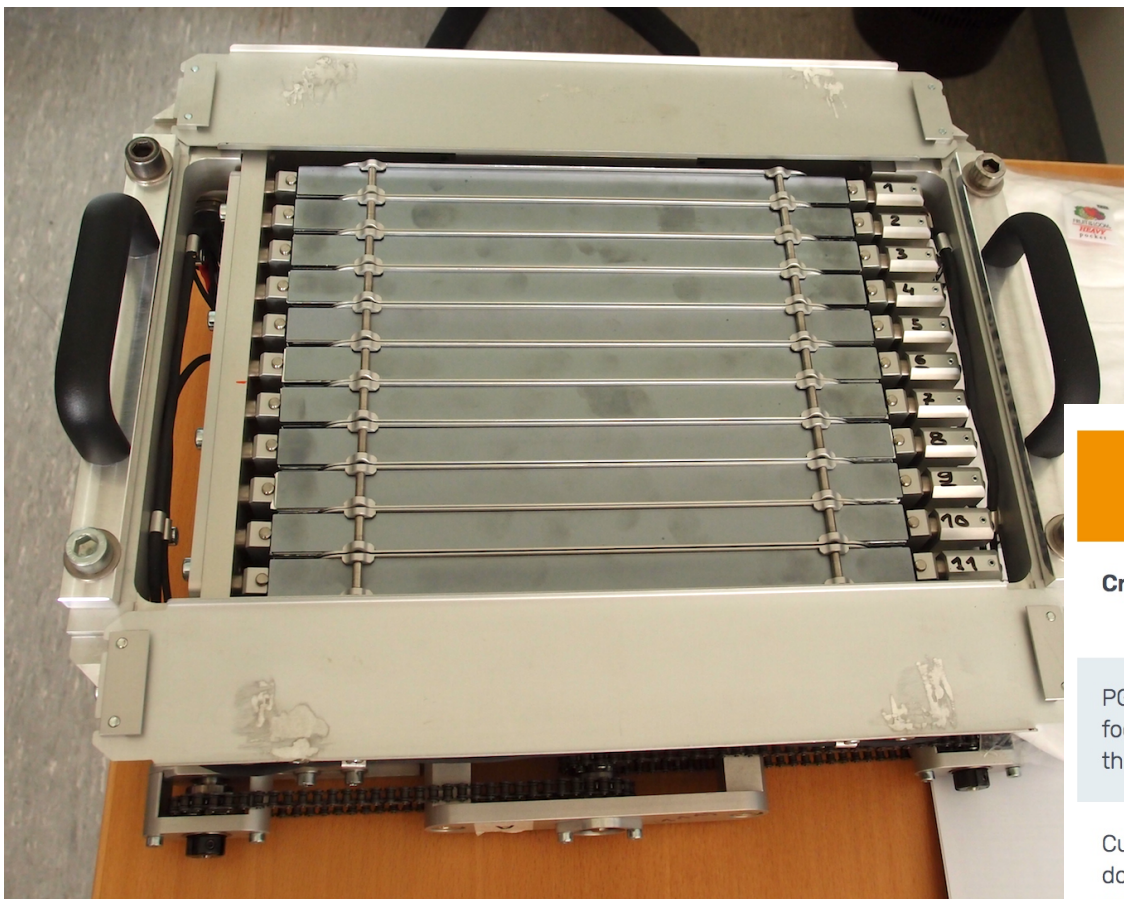
X-ray tests (III)



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Si (111) vers. PG(002)



IN1, IN8, IN20, ThALES

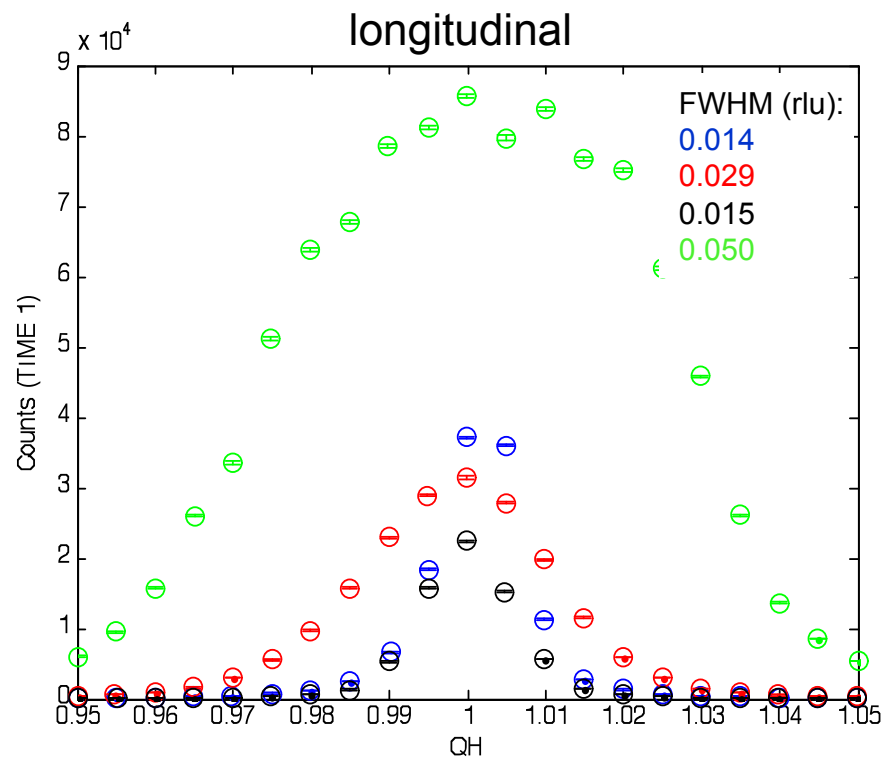
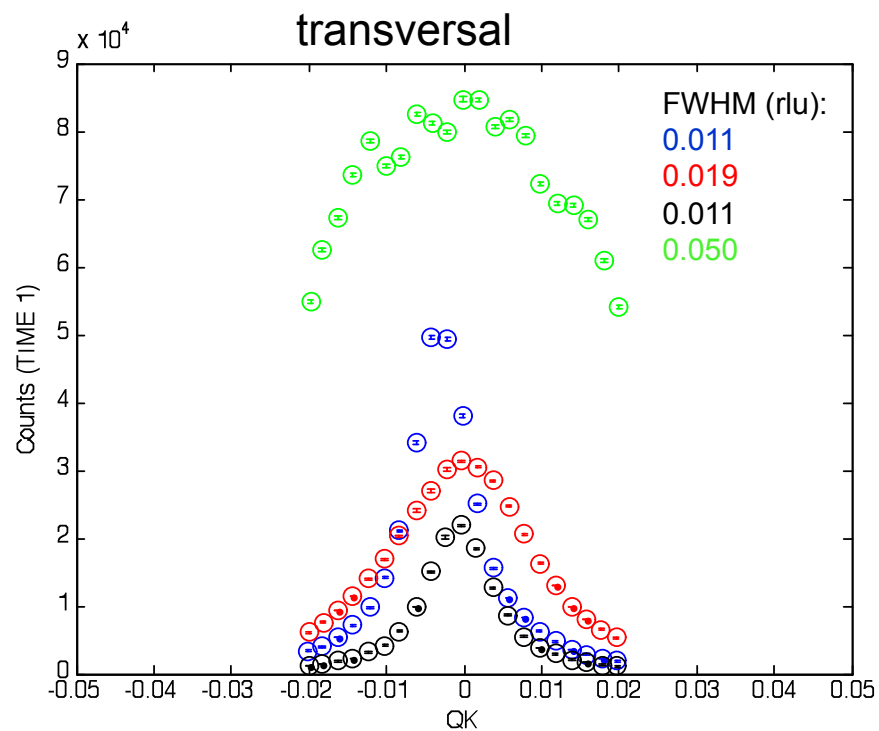
Monochromator

Crystal	W x H (mm ²)	ki/Å ⁻¹	flux/10 ⁸ n cm ⁻² s ⁻¹
PG (002) double focusing, three faces	233x197	2.662 4.1	2.0 6.5
Cu (200) variable double-focusing, anisotropic mosaic (h:25', v:10')	233x197	4.1 7.0	4.6 3.0
Si (111) bent perfect crystals, fixed horiz. curvature optimized for k=3.5Å ⁻¹	180x197	2.662 4.1	0.8 3.4

monochromatic flux \approx 1/3 PG

Si (111) vers. PG(002)

Bragg width (PMN 100)



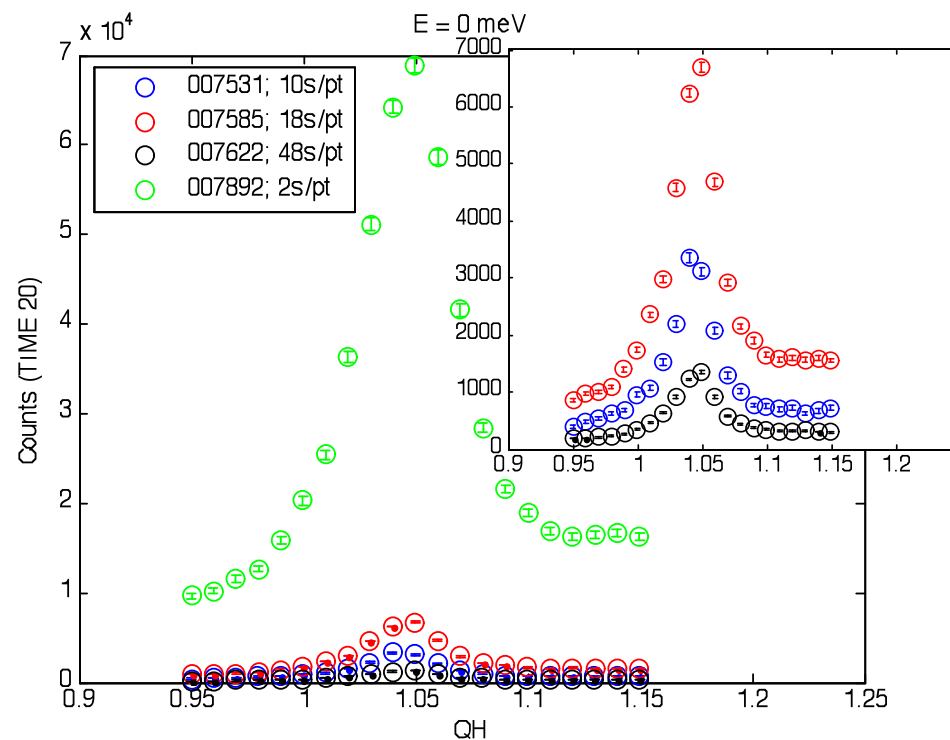
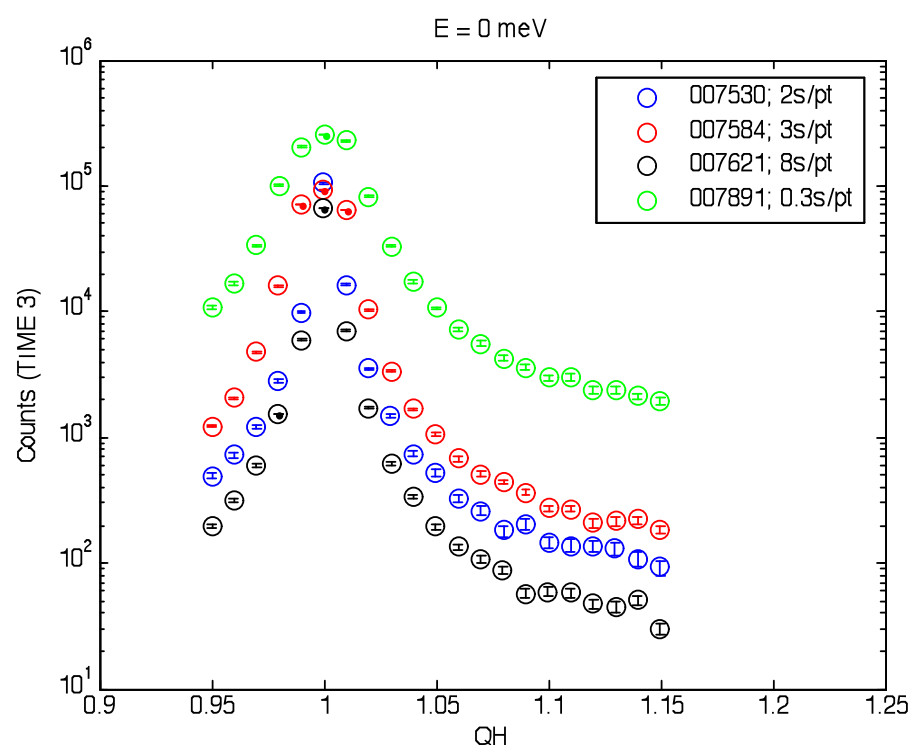
PG-PG	open	DTR 40
PG-PG	40' - 40'	DTR 40
Si-Si	open	DTR 10
Si-Si	40' - 40'	DTR 40

Si (111) vers. PG(002)

Diffuse scattering (PMN 100)

Along diffuse streak
(1+q, -q, 0)

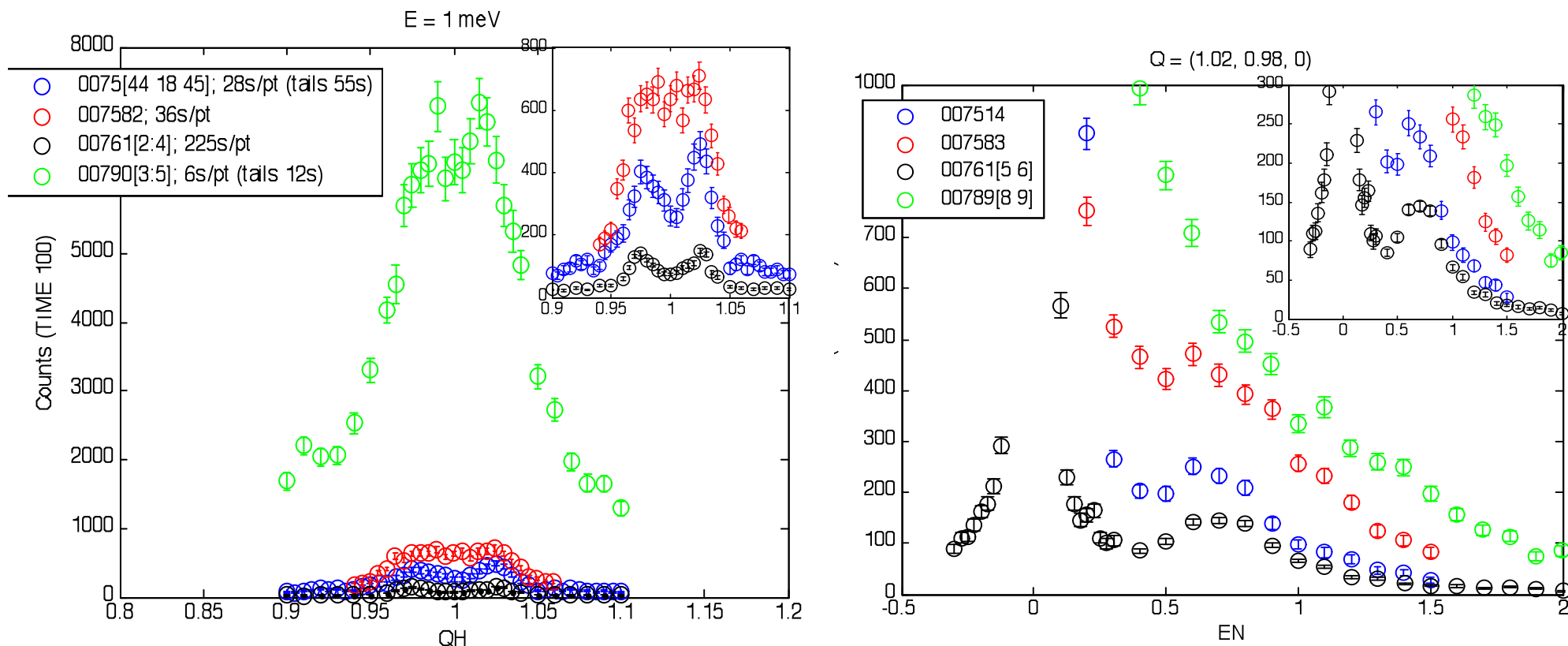
Across diffuse streak
at (1.05, -0.05, 0)



PG-PG	open	DTR 40
PG-PG	40' - 40'	DTR 40
Si-Si	open	DTR 10
Si-Si	40' - 40'	DTR 40

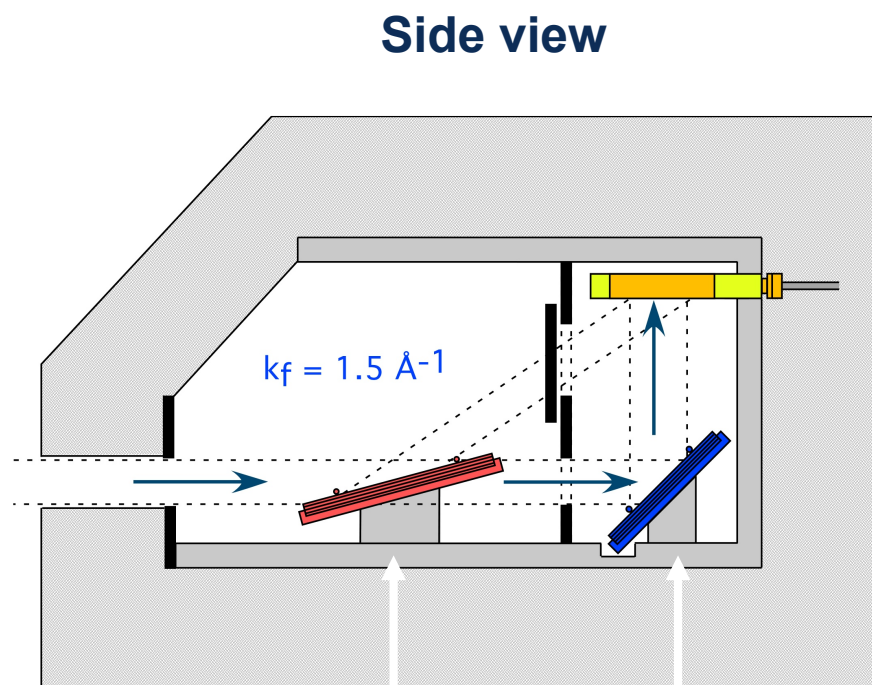
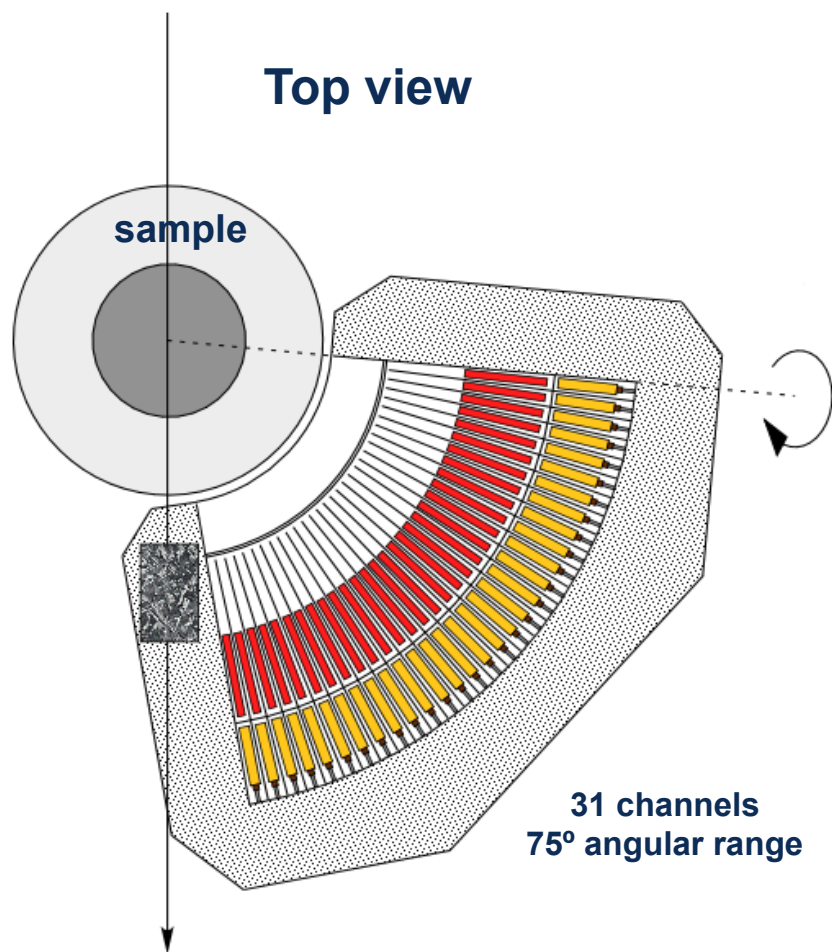
Si (111) vers. PG(002)

Phonons & QE signal (PMN 110)



PG-PG	open	DTR 40
PG-PG	40' - 40'	DTR 40
Si-Si	open	DTR 10
Si-Si	40' - 40'	DTR 40

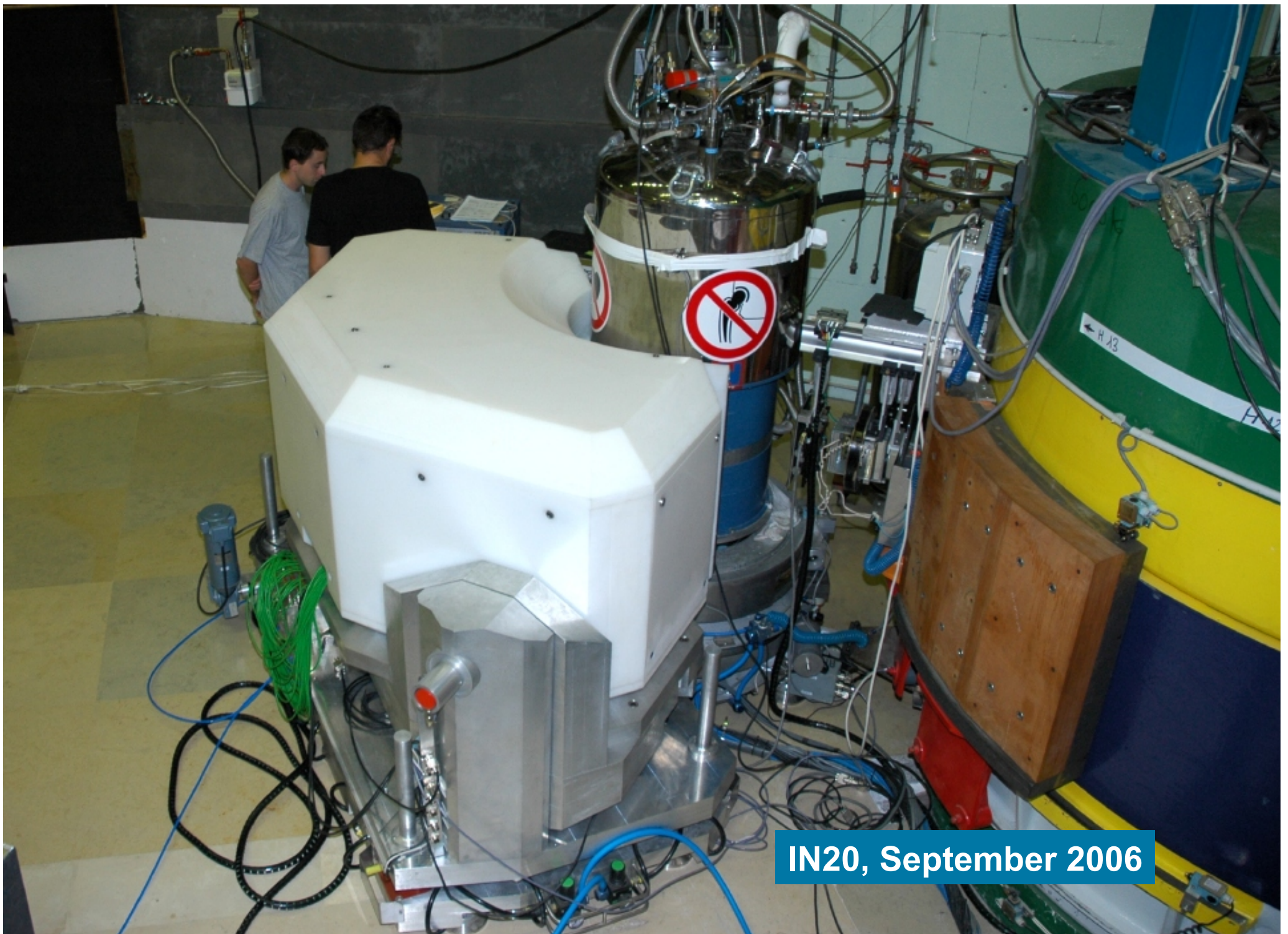
FlatCone multianalyzer



$k_f = 3 \text{ \AA}^{-1}$

$k_f = 1.5 \text{ \AA}^{-1}$

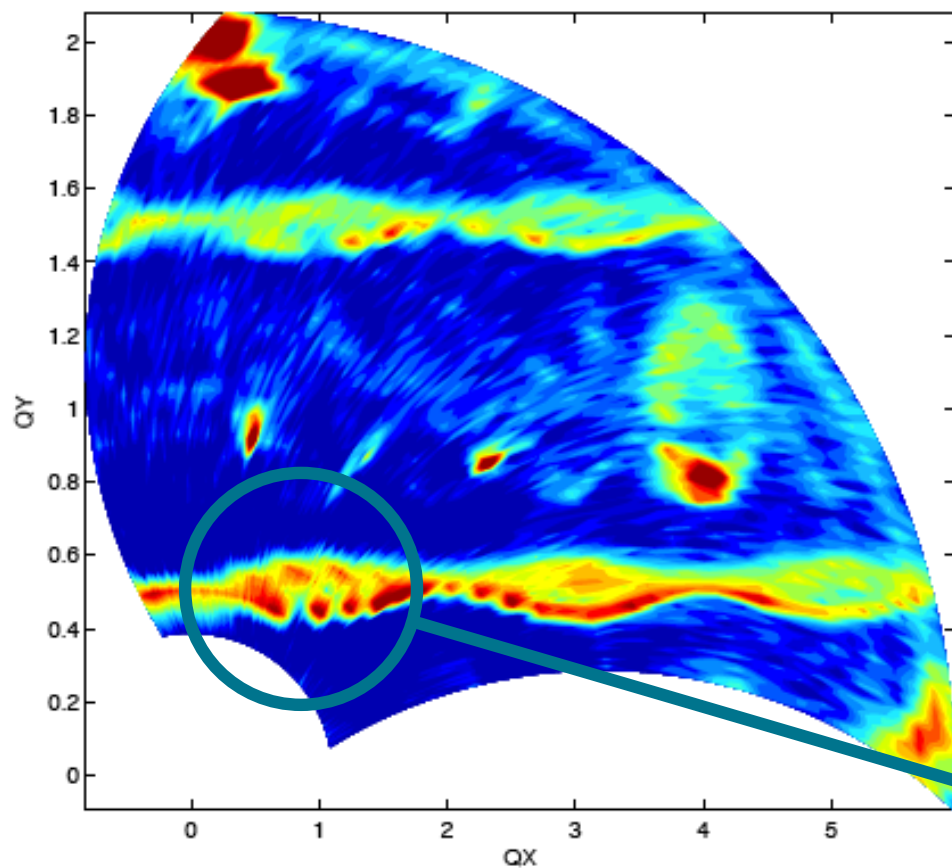




IN20, September 2006

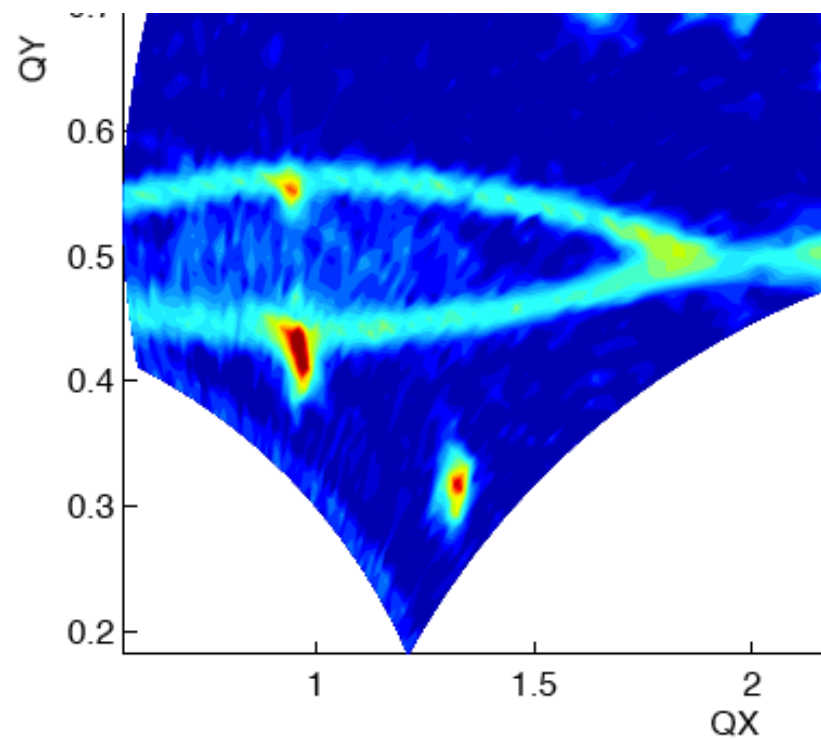
CuGeO₃

CuGeO₃, En= 5, MN=500, A_{ref} = 50.74 (#043558)

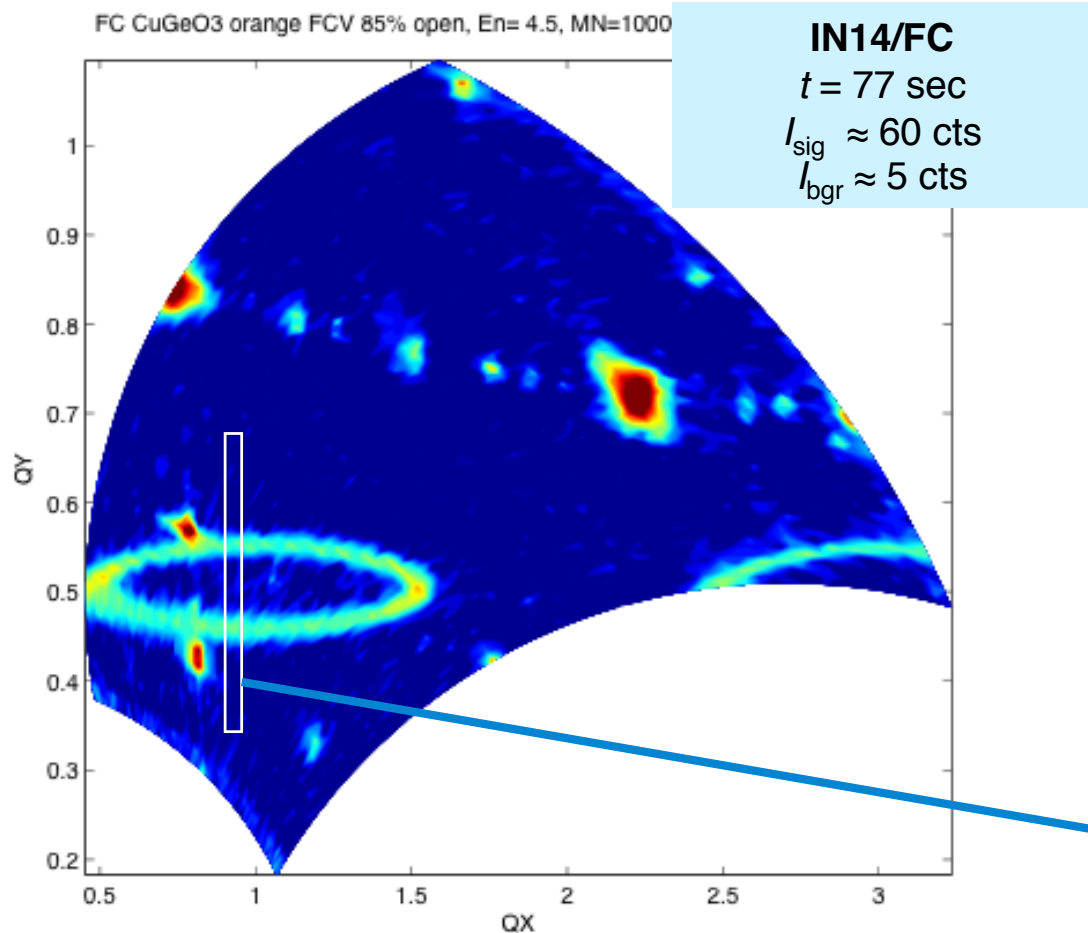


THERMAL NEUTRONS
 $k_f = 1.4 \text{ \AA}^{-1}$

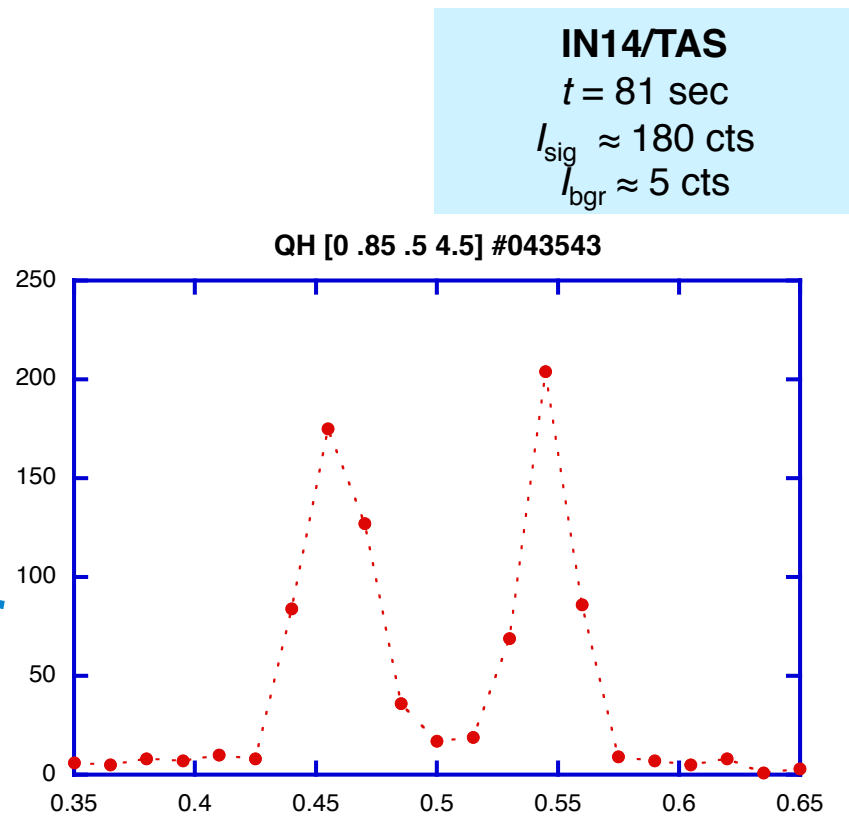
COLD NEUTRONS
 $k_f = 1.4 \text{ \AA}^{-1}$



CuGeO₃ with IN14/FC



$\Delta E = 4.5$ meV
 $k_f = 1.4 \text{ \AA}^{-1}$

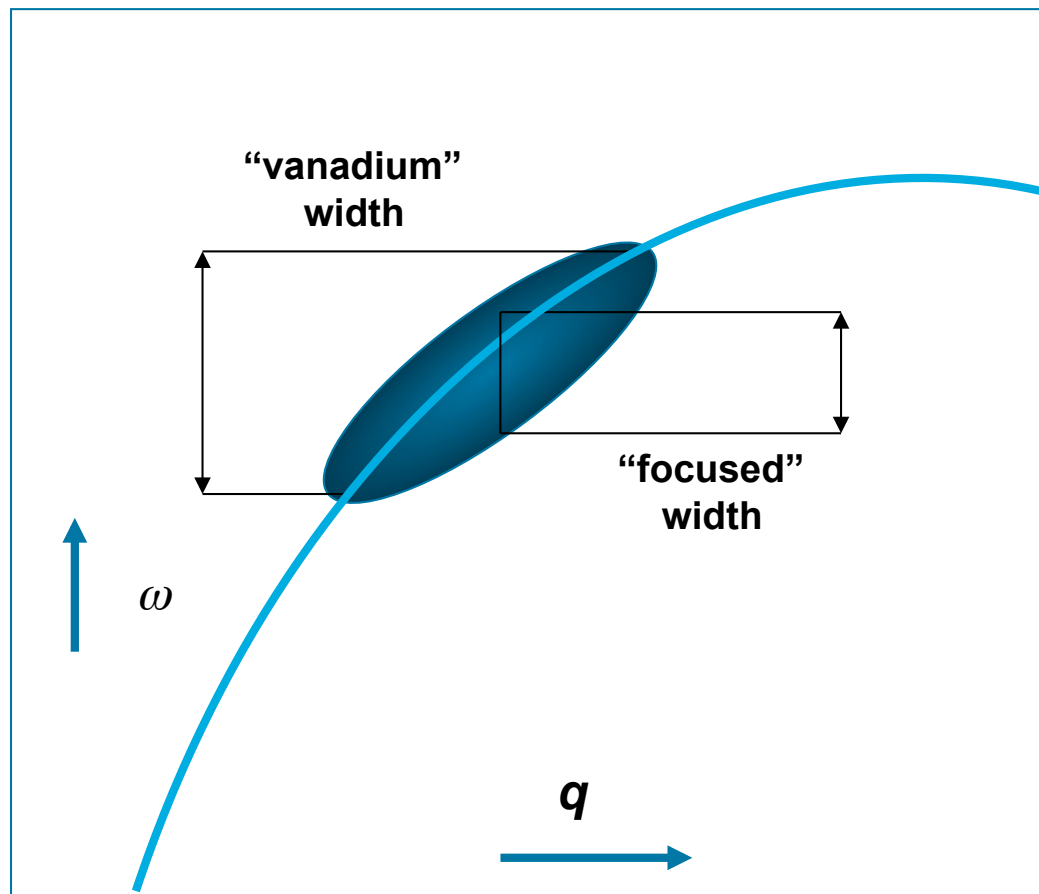


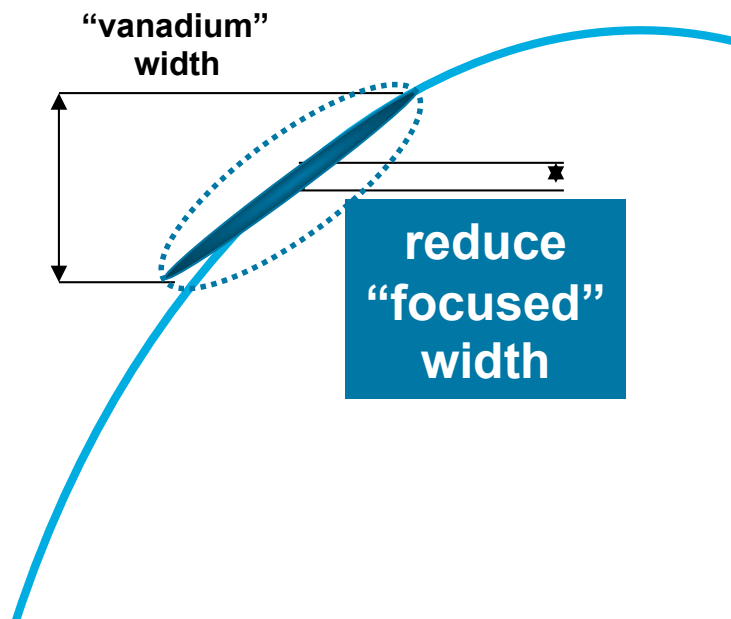
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Neutron Three-Axis Spectrometers:

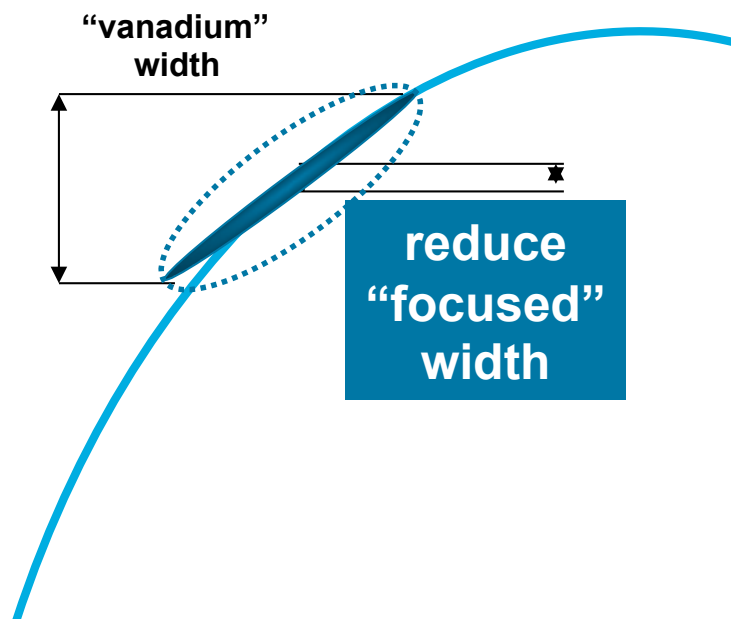
- access to large Q, ω range
- energy resolution $\Delta E/E \approx 5-10\%$
- efficient for $\omega(q)$
- lacking resolution for $\Gamma(q)$



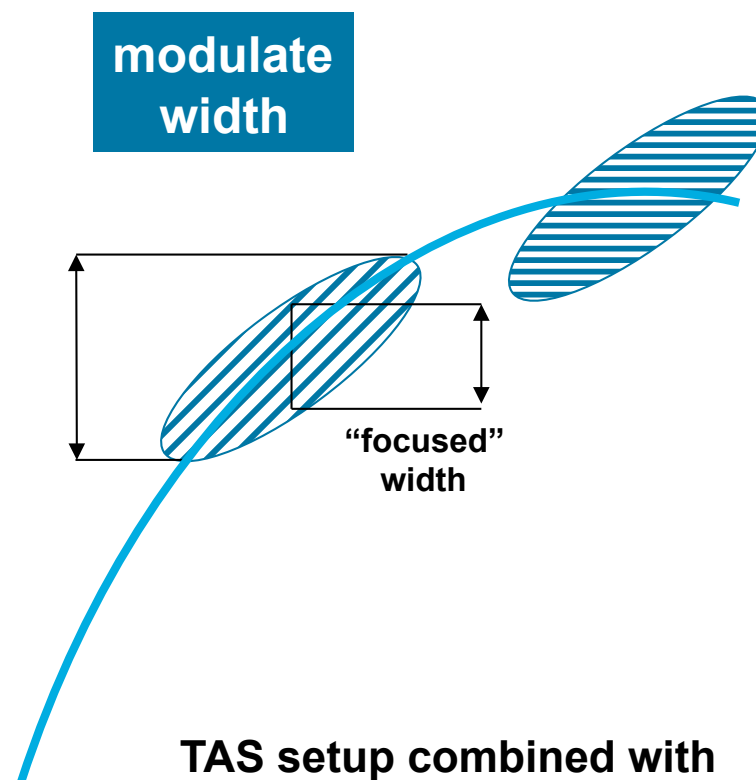


**normal TAS setup with
perfect monochromator &
analyzer crystals (Si, Ge)**

TAS resolution

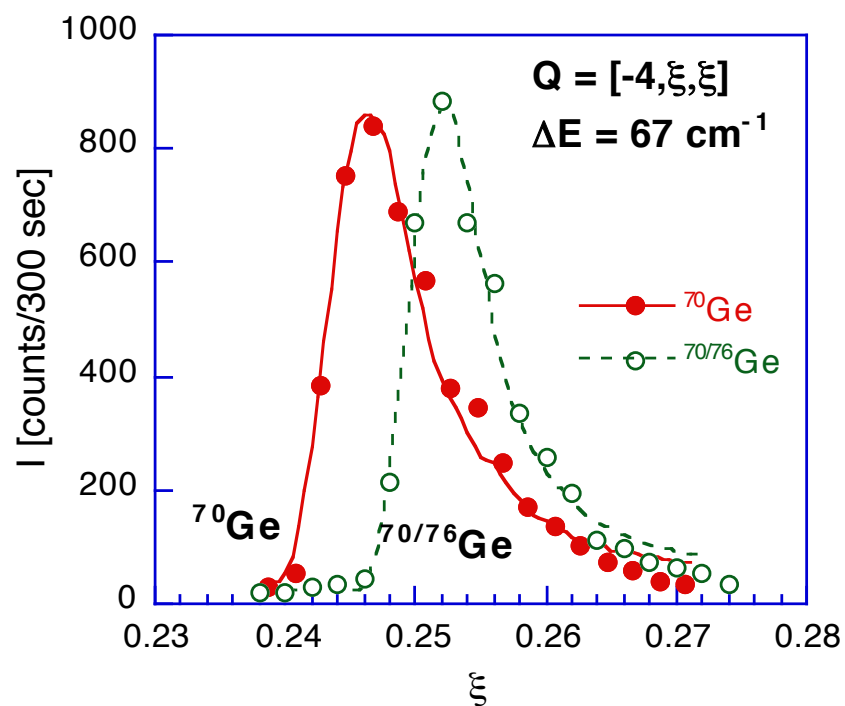


normal TAS setup with
perfect monochromator &
analyzer crystals (Si, Ge)



TAS setup combined with
spin-echo
(TOF Fourier technique)

TASSE vers. high resolution TAS



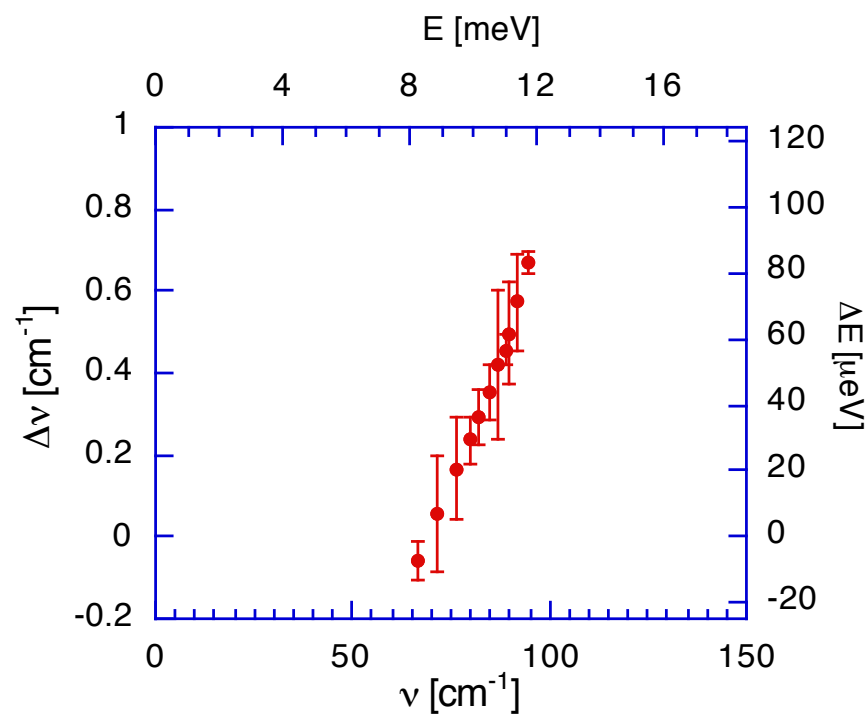
- *same position accuracy*
- *HR TAS faster and easier*
- *TASSE better for FWHM*

IN20

Si111/Si111

$R_M = R_A = 50 \text{ m}$

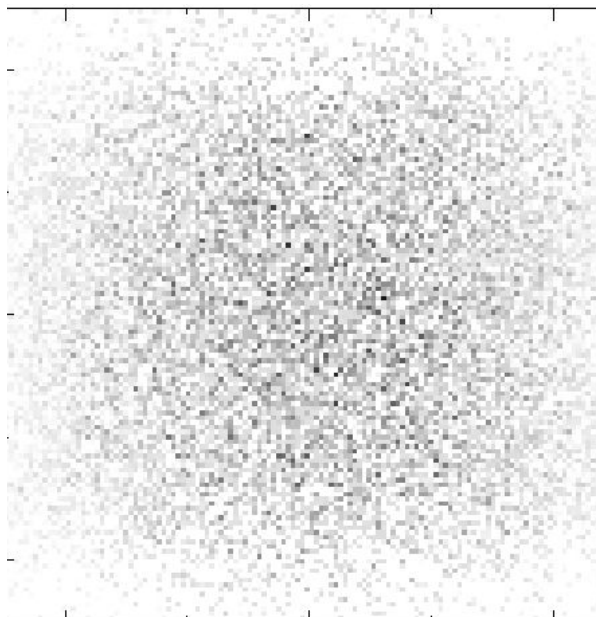
sample volume $< 0.5 \text{ cm}^3$



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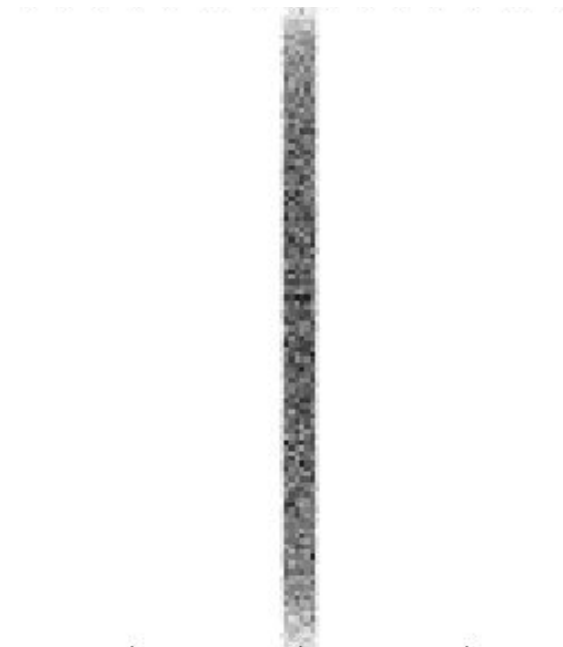
Microfocusing crystal optics



**PG002 horizontal focus
(RESTRAX ray-tracing)**



**Paris-Edinburgh
High pressure cell**



**Si111 horizontal focus
(RESTRAX ray-tracing)**

Si (111) microfocusing tests

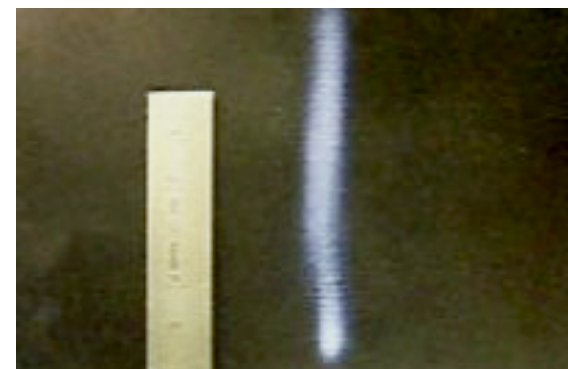
IN20 (2009)

horizontal (focused)

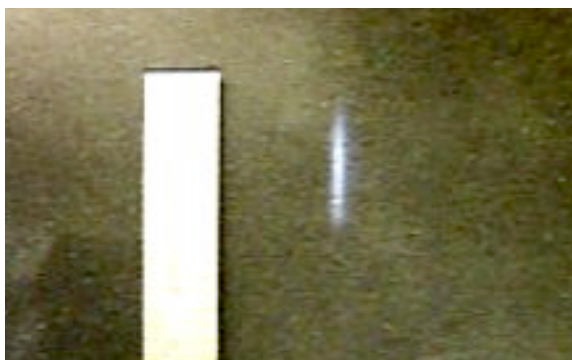


$D \approx 10 \text{ mm}$

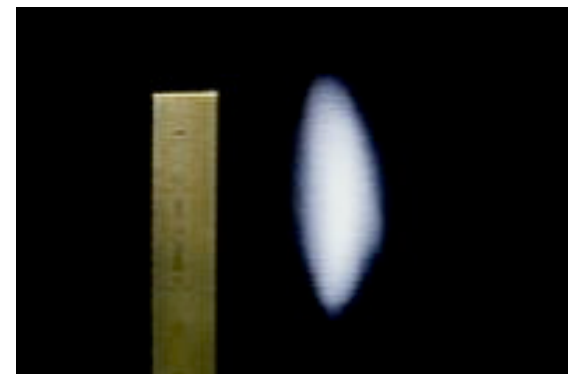
vertical ($D \approx 2 \text{ mm}$)



defocused

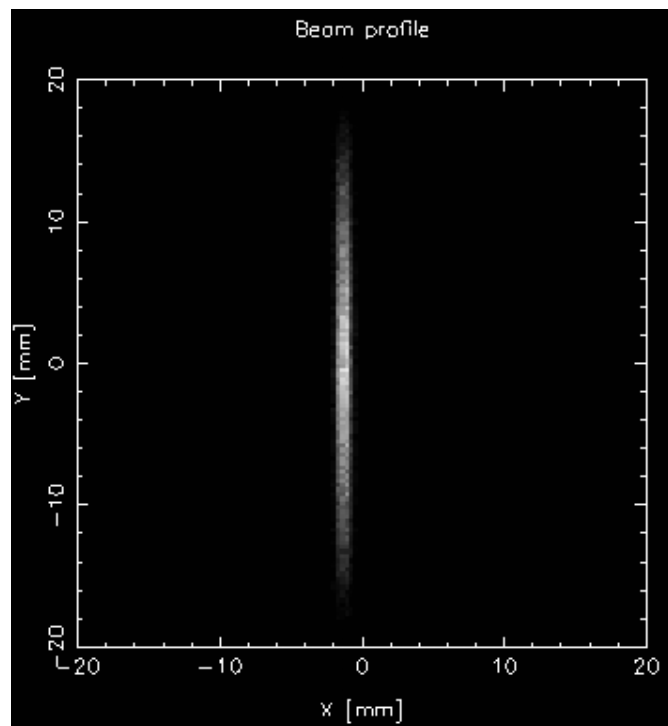


$D \approx 1 \text{ mm}$



focused

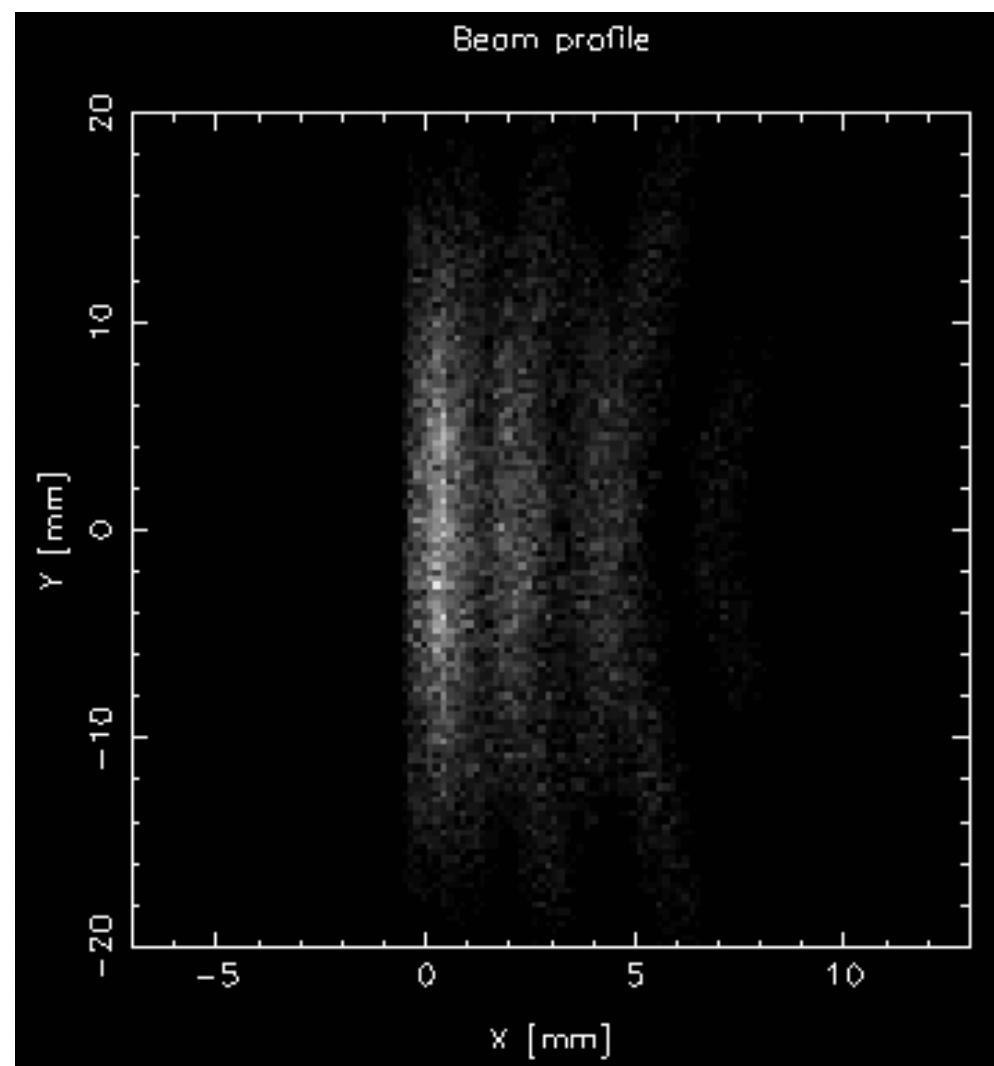
Vertical focusing Si111



1 segment

Restrax simulation
real space (X-Y)

9 segments

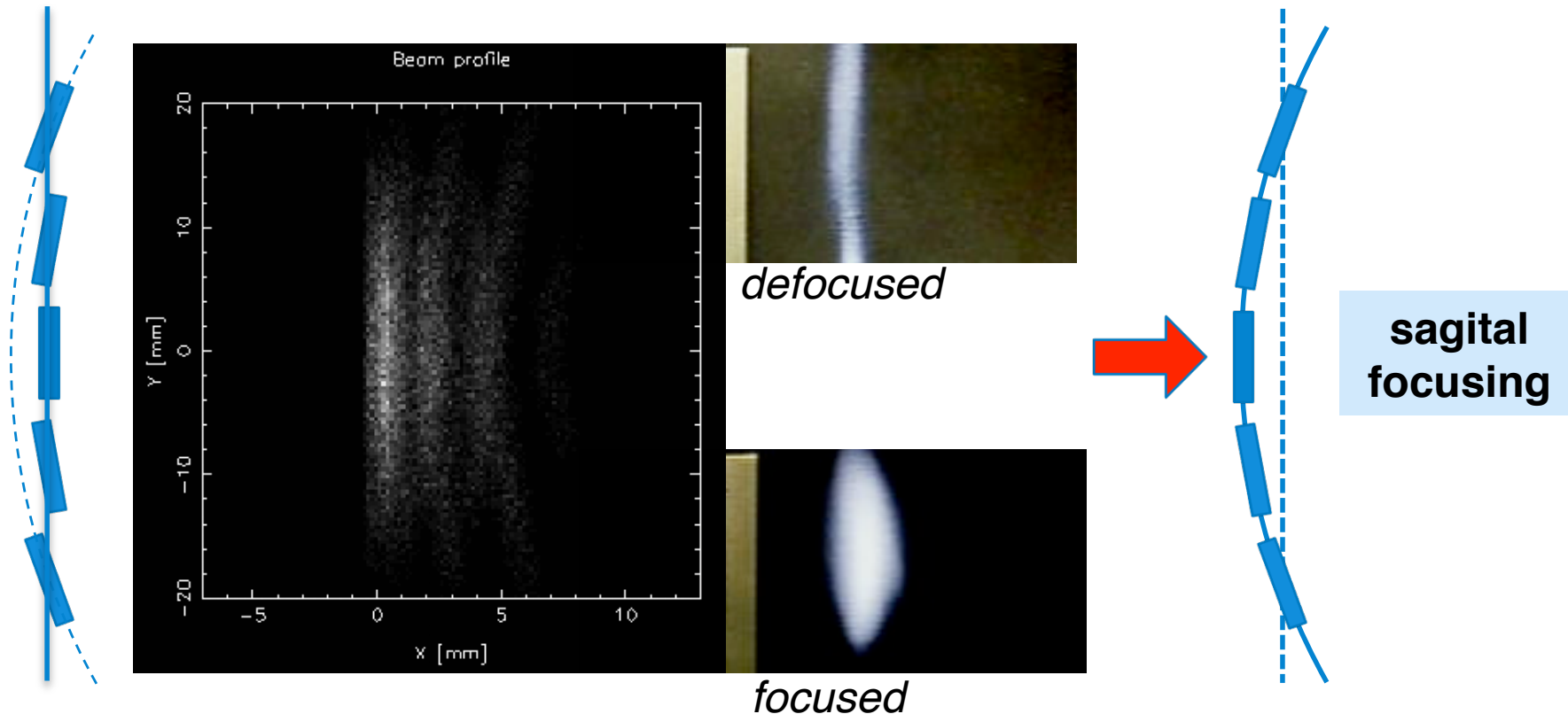


Vertical focusing aberrations

- standard TAS devices approximate cylindrical surface by a flat array of tilted slabs
- in high resolution mode aberrations due to variations in θ_B become apparent

➔ **develop a true sagittally focusing system**

➔ **replace by a multichannel supermirror device**



Concluding remarks

Strong points

- deterministic behavior, sharp imaging
- almost rectangular reflection profiles
- absence of 2nd order contamination (Si, Ge, diamond)
- high transparency if Si (multicrystal alignments)

Caveats

- needs precise manufacturing/alignment
- reveals irregularities of samples (sample assemblies)
- aberrations visible in high-resolution setups
- silicon cutting issues